



**Research Institute for Technical Physics and Materials
Science of the Hungarian Academy of Sciences**



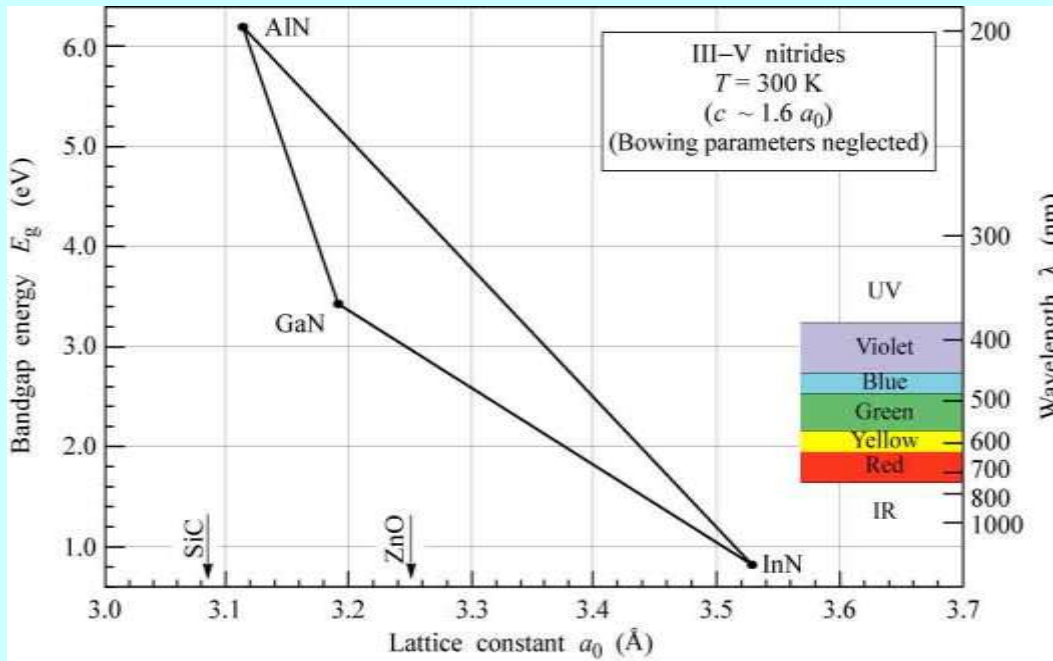
Széles tiltottsávú félvezetők, a kék LED-en túl

Pécz Béla

MTA EK MFA



2018. december 12
Fizikai Tudományok Osztálya



$$E = hc/\lambda$$

High power devices

optoelectronics

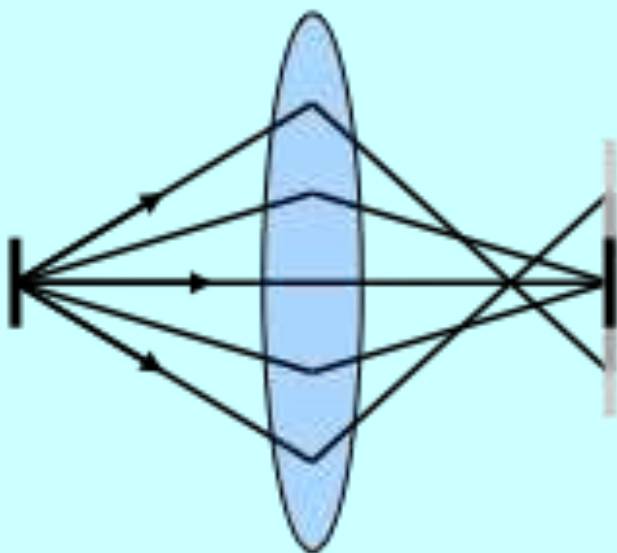
blue LED---> Nobel prize 2014



*Isamu Akasaki, Hiroshi Amano
and Shuji Nakamura*

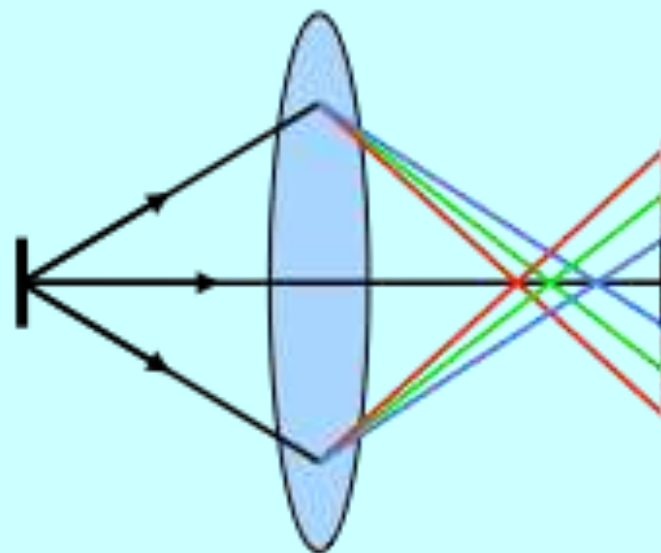


Lencsehibák



Gömbi hiba
feloldás határ

$$R_m/M = r_s = C_s \alpha^3$$



Szín hiba
információ határ

$$R_c/M = r_c = C_c \cdot \alpha \cdot \Delta E/E$$

vastag minta...

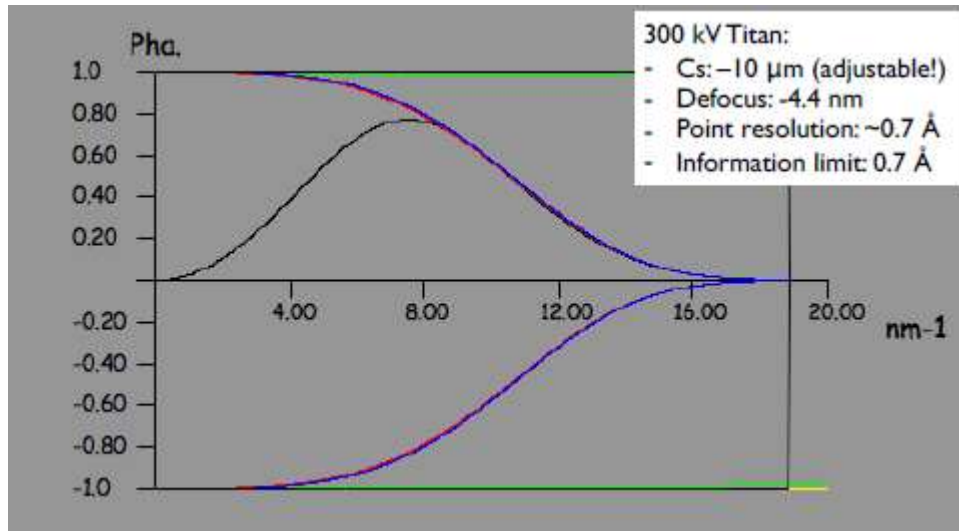
Room temperature variations

0.2 °C/60min

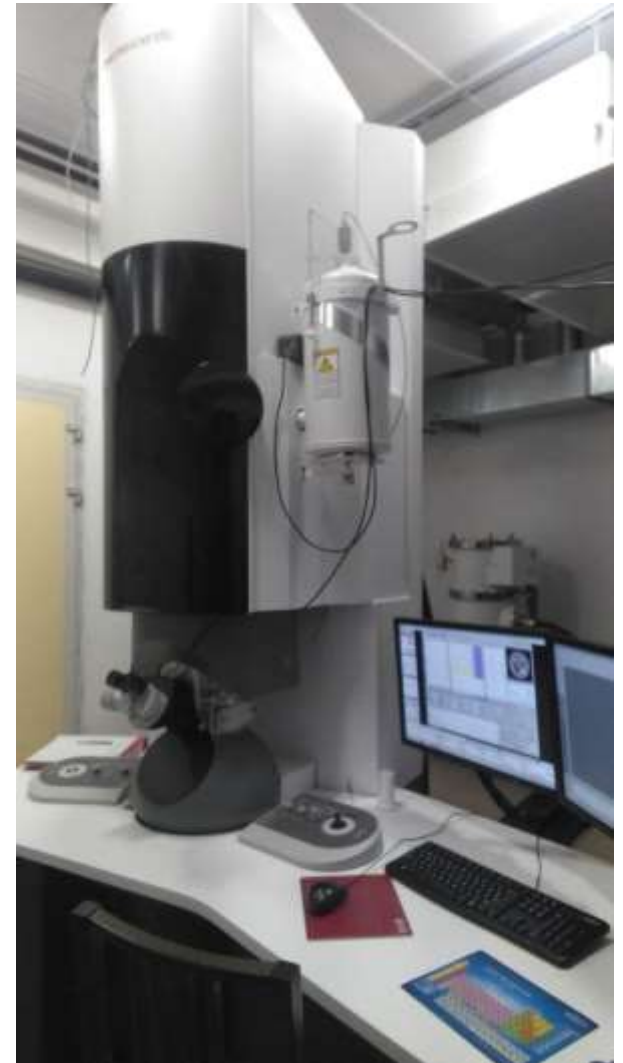
0.1 °C/30min

Air velocity: <5m/min.

Stray magnetic field (50 Hz): 30nT p-p.



THEMIS 200 image corrected



Rayleigh criterion for VLM

$$\delta = \frac{0.61\lambda}{\mu \sin \beta}$$

Optical microscope: 200 nm resolution

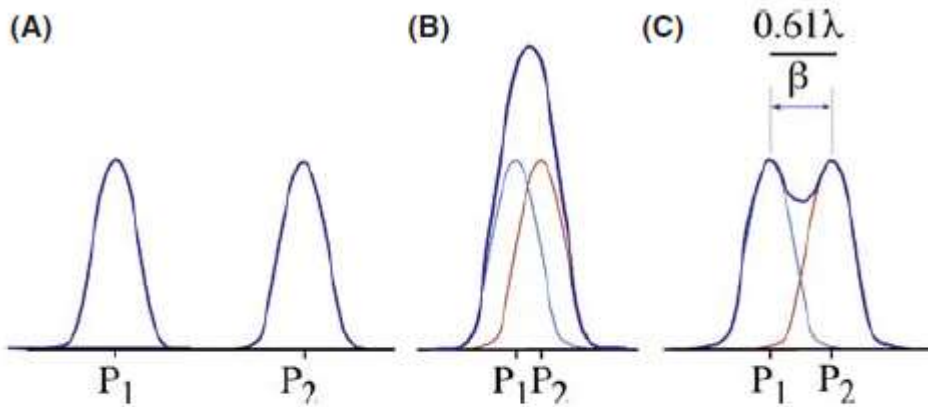
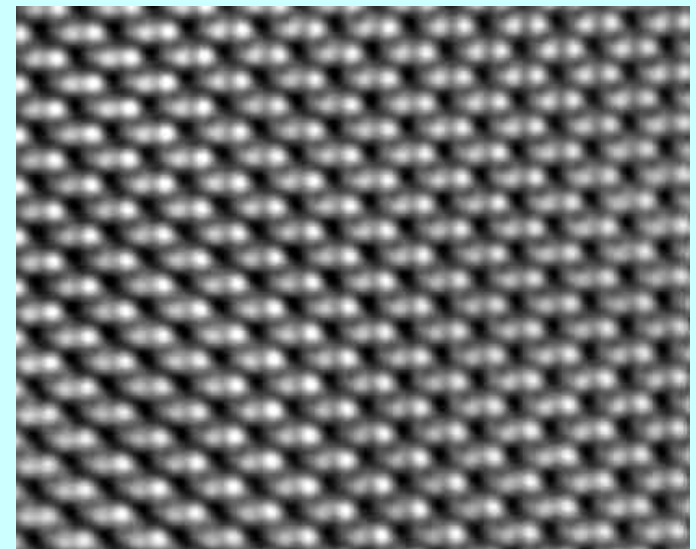
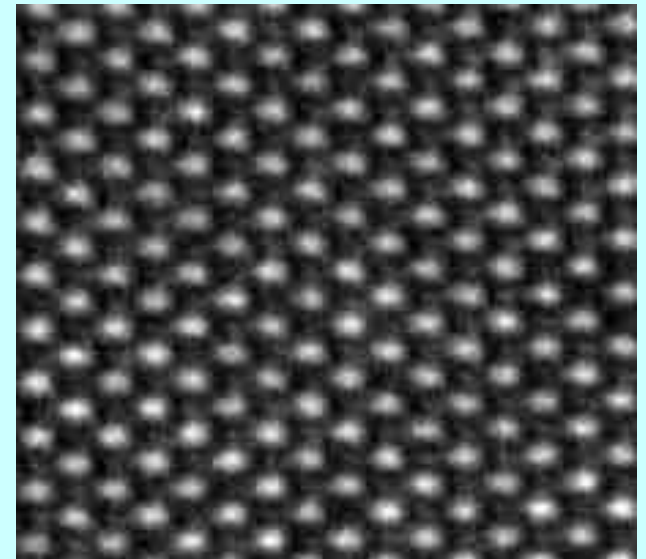


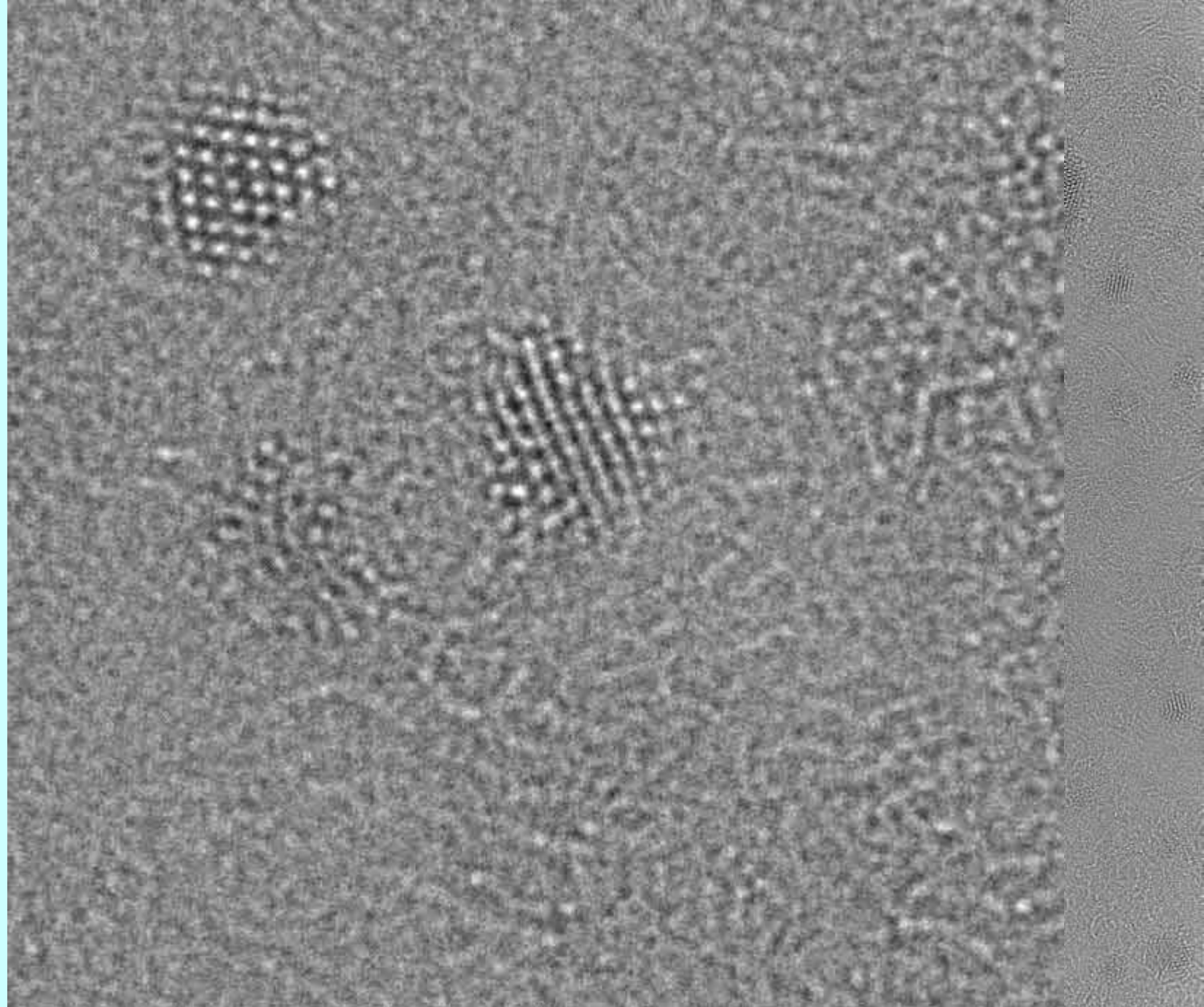
FIGURE 6.14. (A) The Airy-disk intensity profiles from two clearly separated point sources P_1 and P_2 . In (B) the two Airy disks are so close that they cannot be distinguished, but in (C) the two are separated such that the maximum in the image of P_1 overlaps the minimum in P_2 . This latter situation is the definition of resolution defined by the Rayleigh criterion and is the best (diffraction-limited) resolution.

$$\lambda = \frac{h}{p}$$

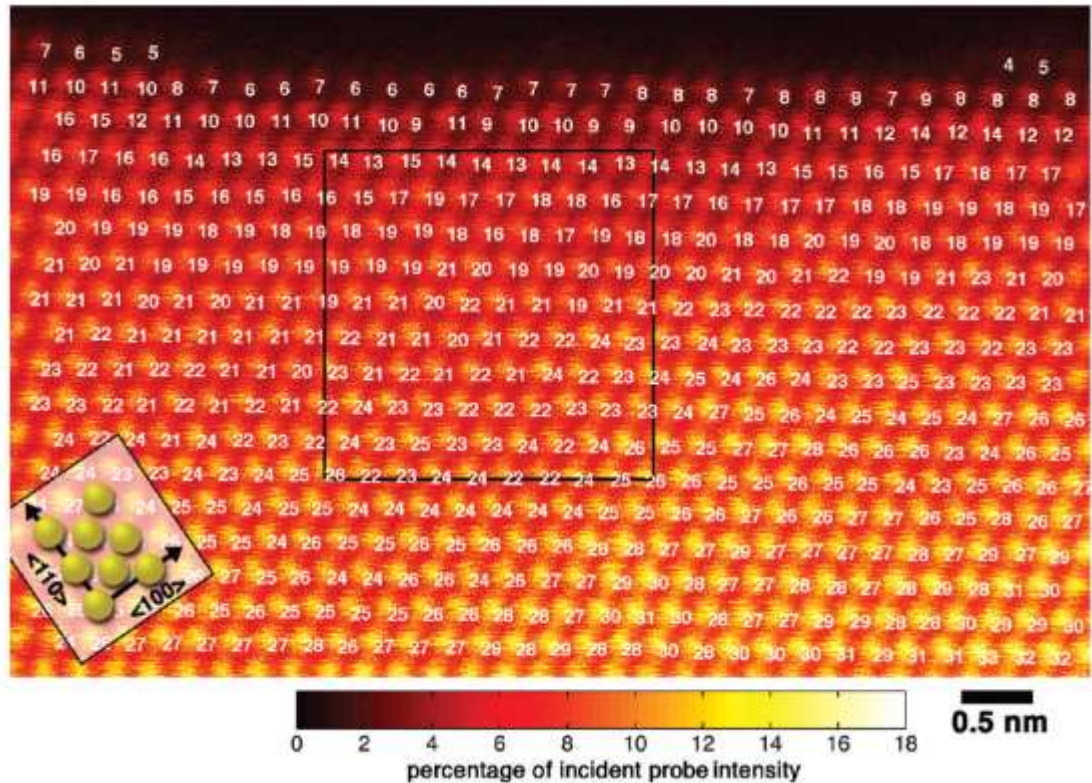
$$\lambda = \frac{h}{\left[2m_0eV\left(1 + \frac{eV}{2m_0c^2}\right)\right]^{1/2}}$$

diamond dumbbells 89 pm



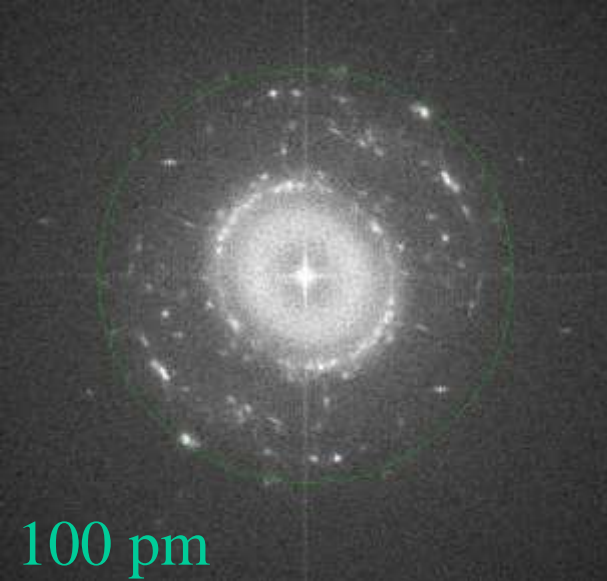


10 nm



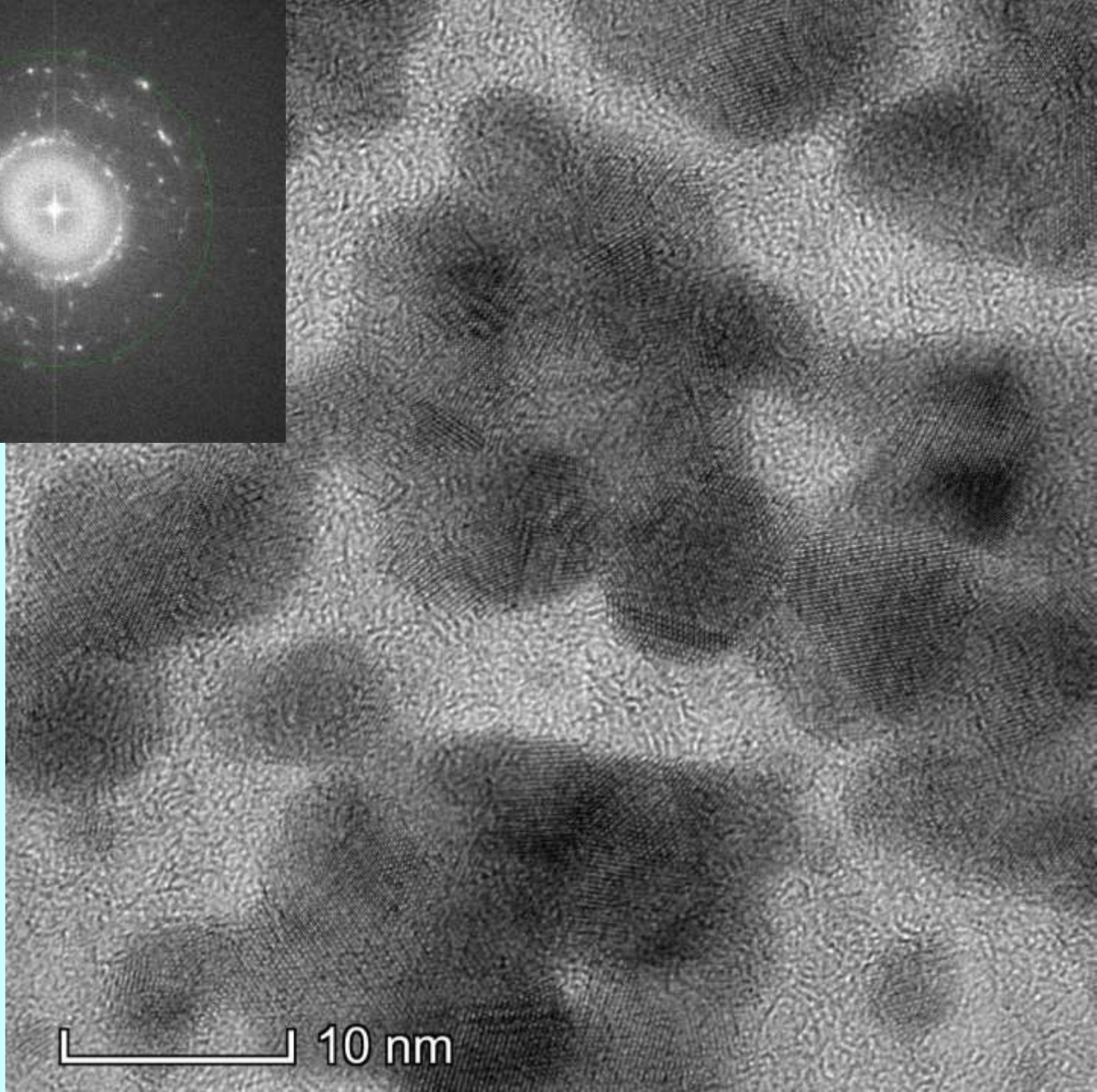
DOI: 10.1021/nl102025s | *Nano Lett.* **2010**, *10*, 4405--4408

number of gold atoms in columns

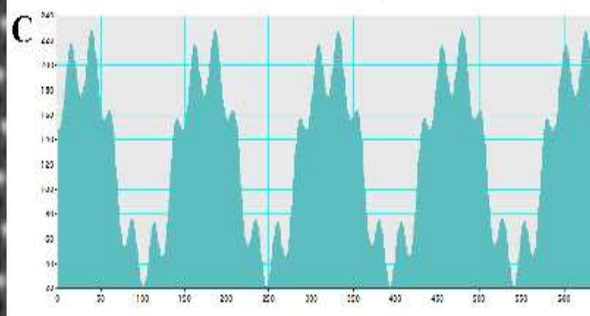
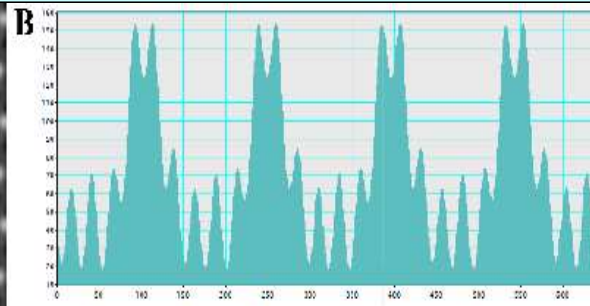
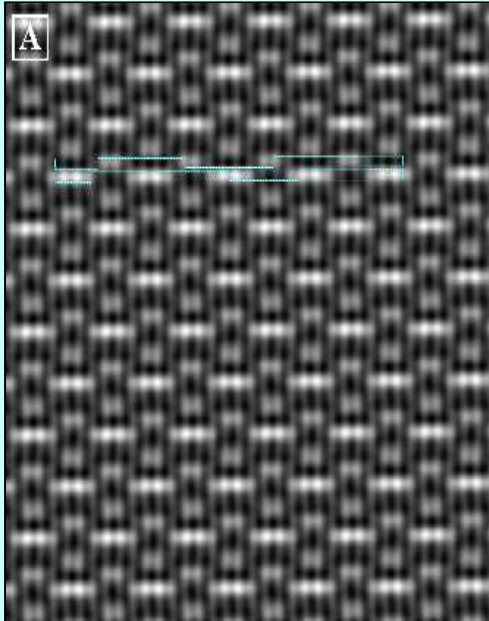


100 μm

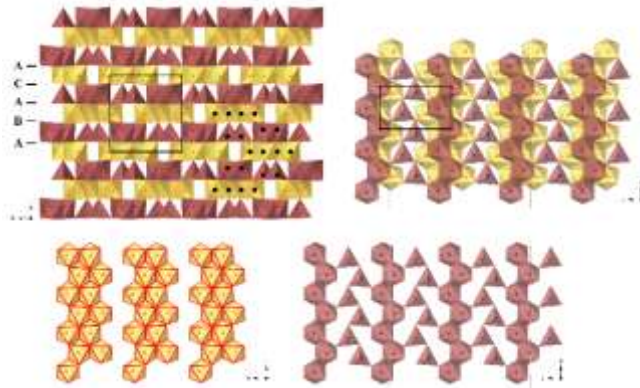
80 keV



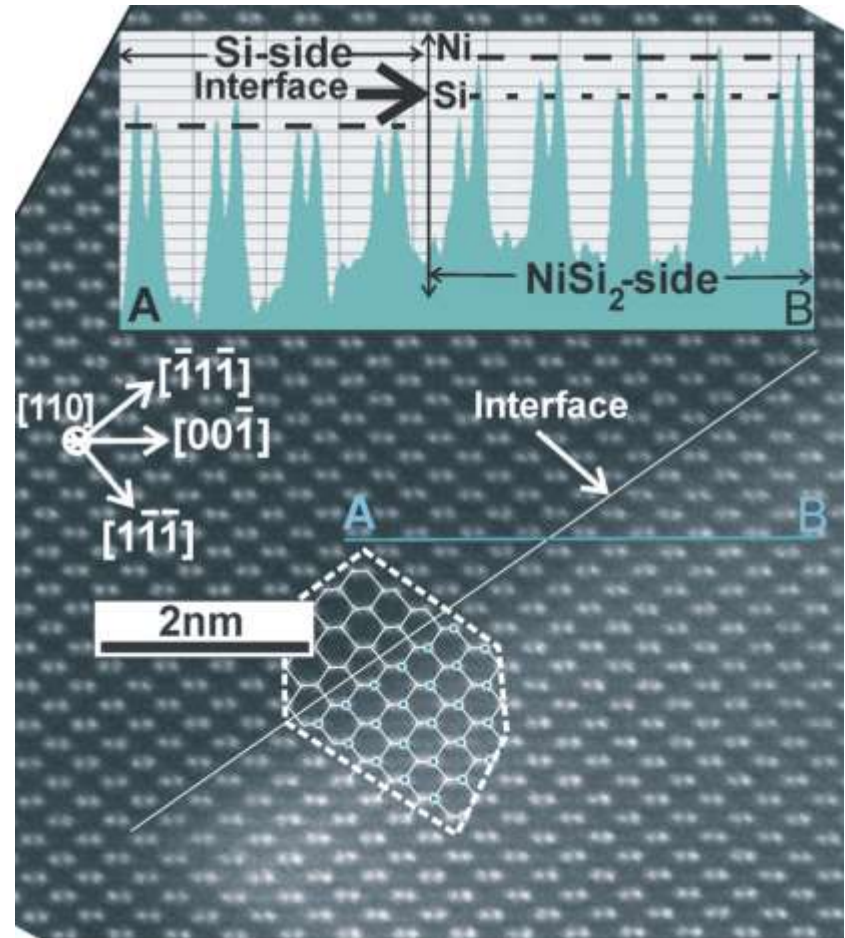
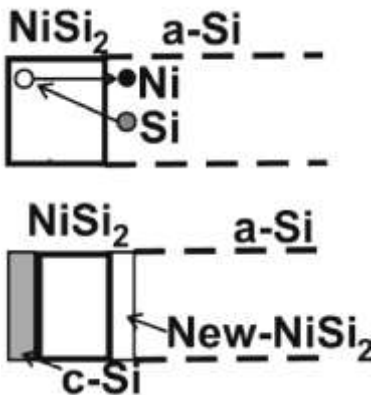
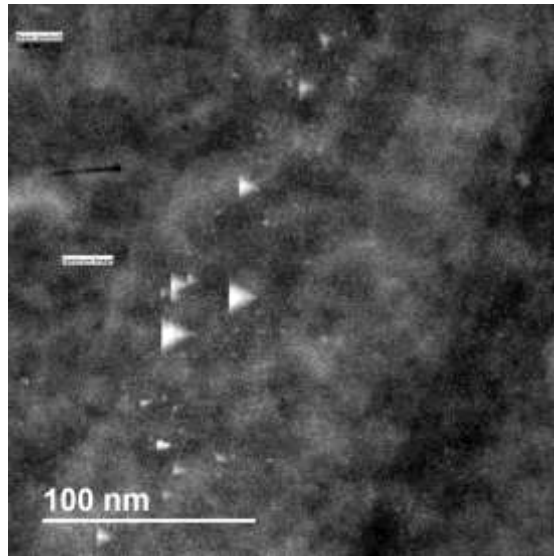
10 nm



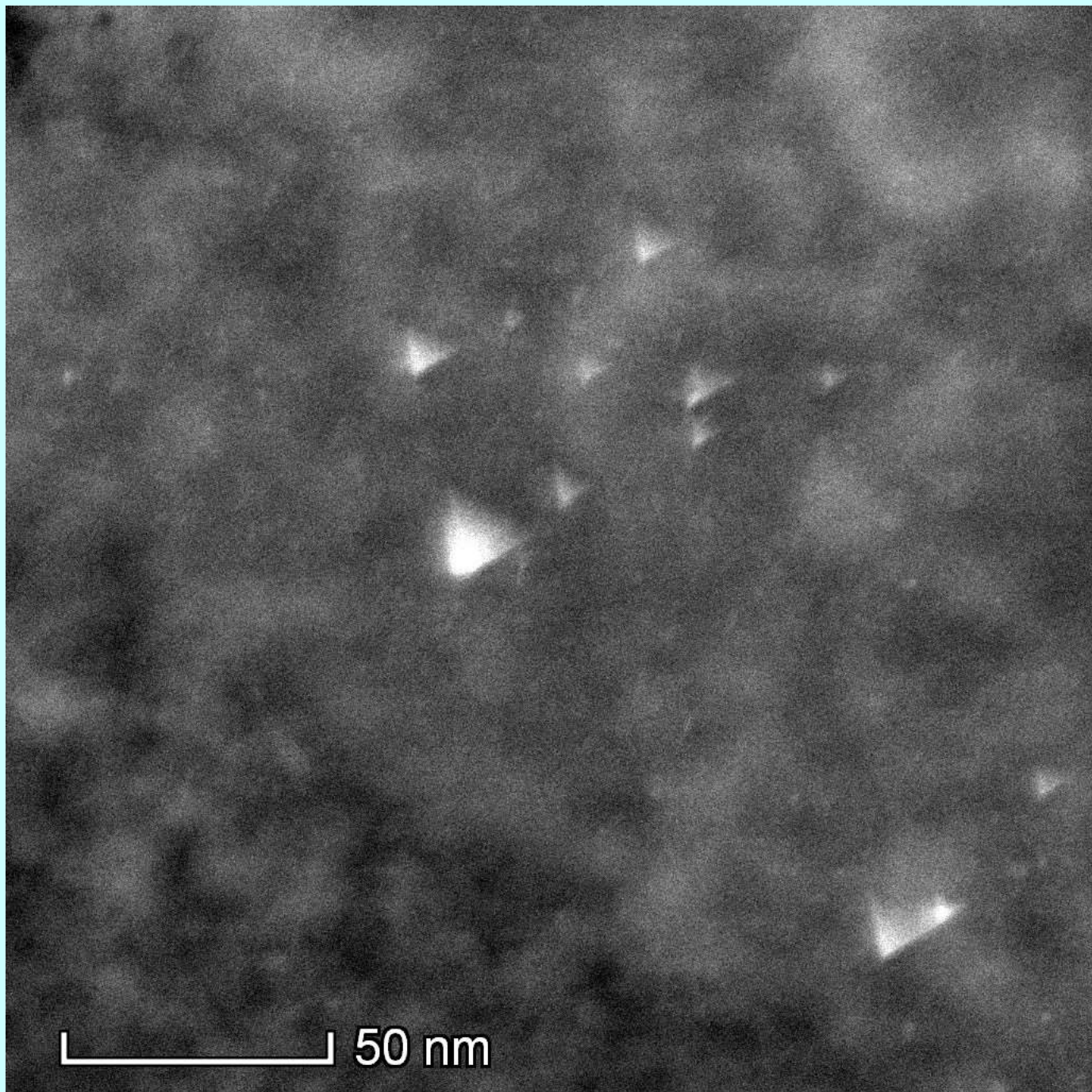
I. Cora et al. CrystEngComm.
2017, 19, 1509-1516



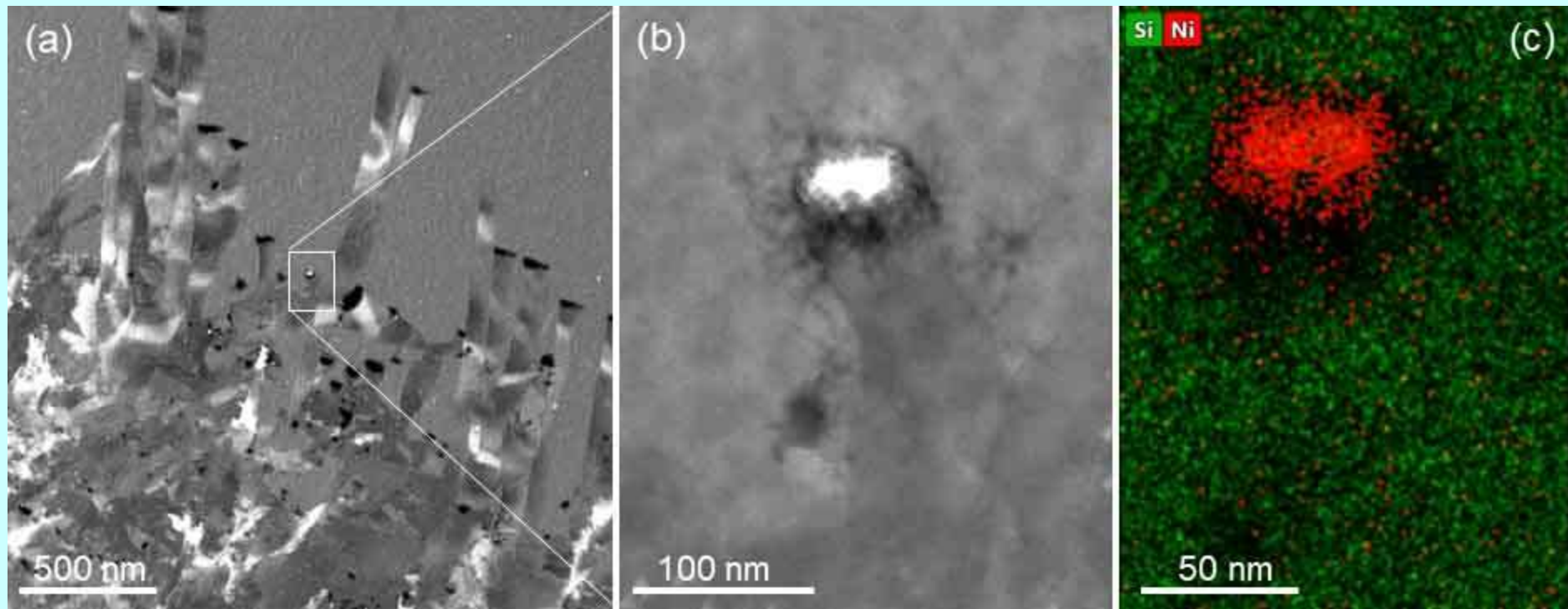
Octahedra and tetrahedra
ribbons give the precise 2:3
Ga:O ratio



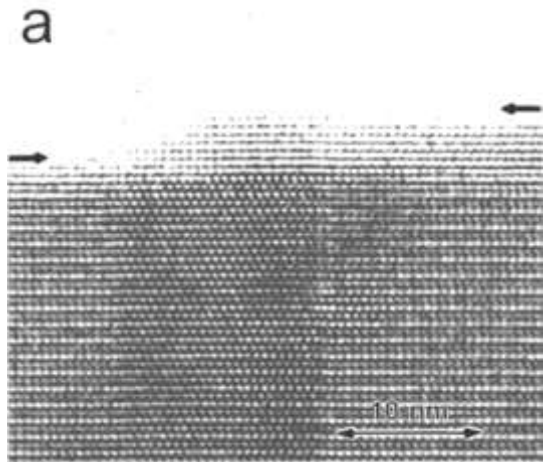
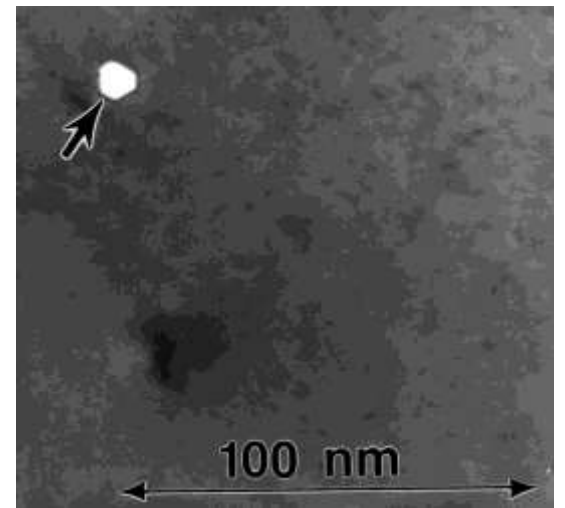
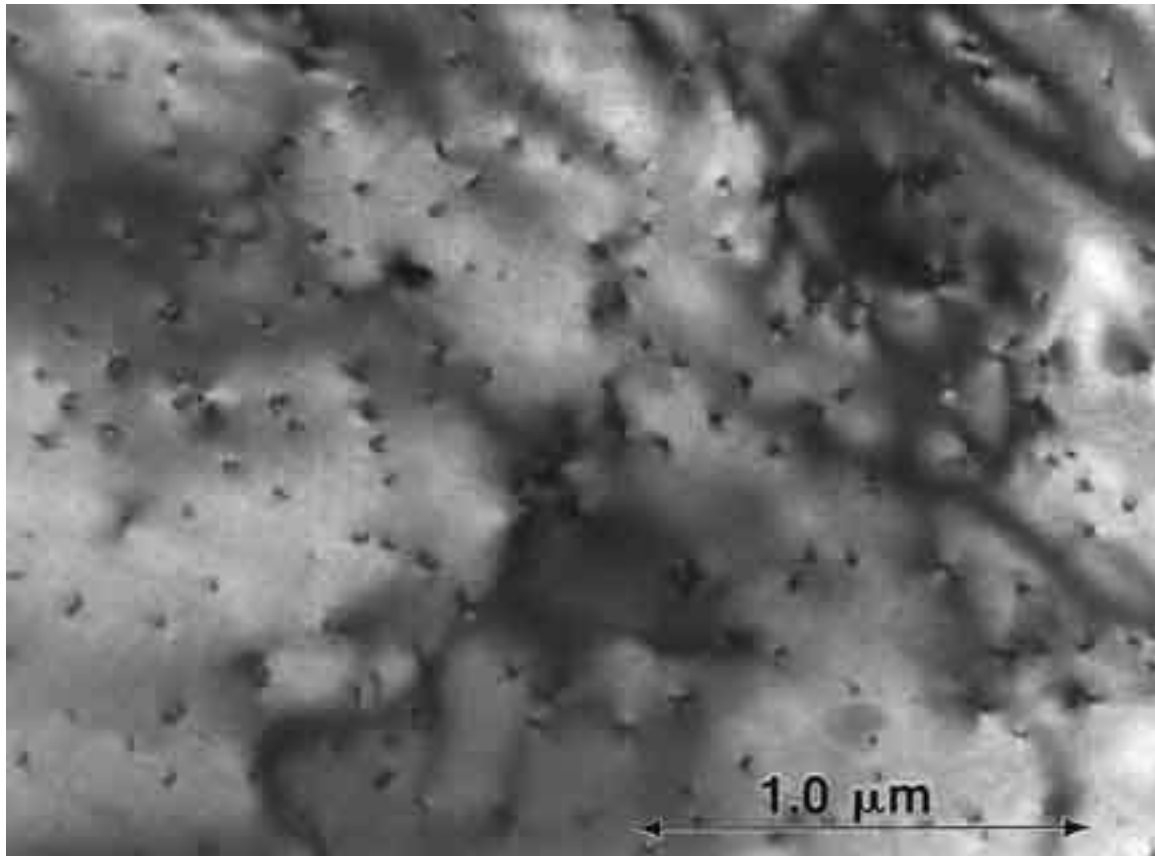
G.Z. Radnóczy, D. Knez, F. Hofer, N. Frangis, N. Vouroutzis, J. Sttoimenos, B. Pécz.
 JOURNAL OF APPLIED PHYSICS 121, 145301 (2017)



50 nm



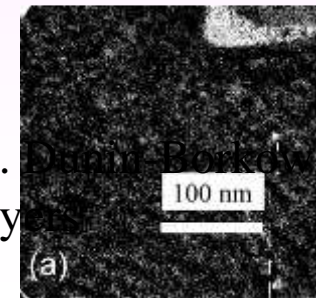
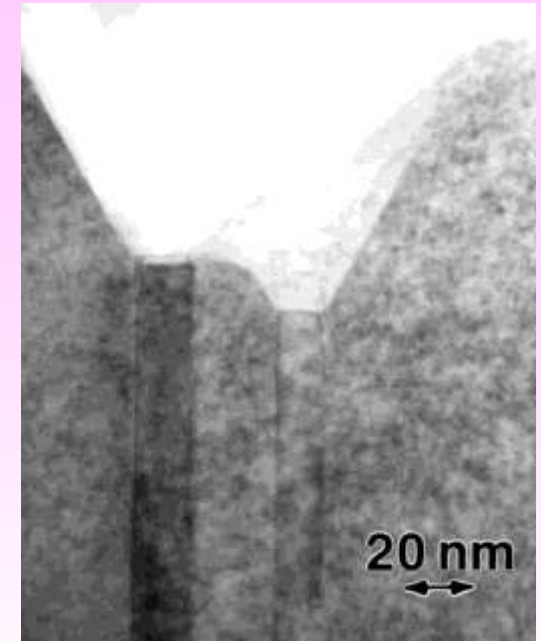
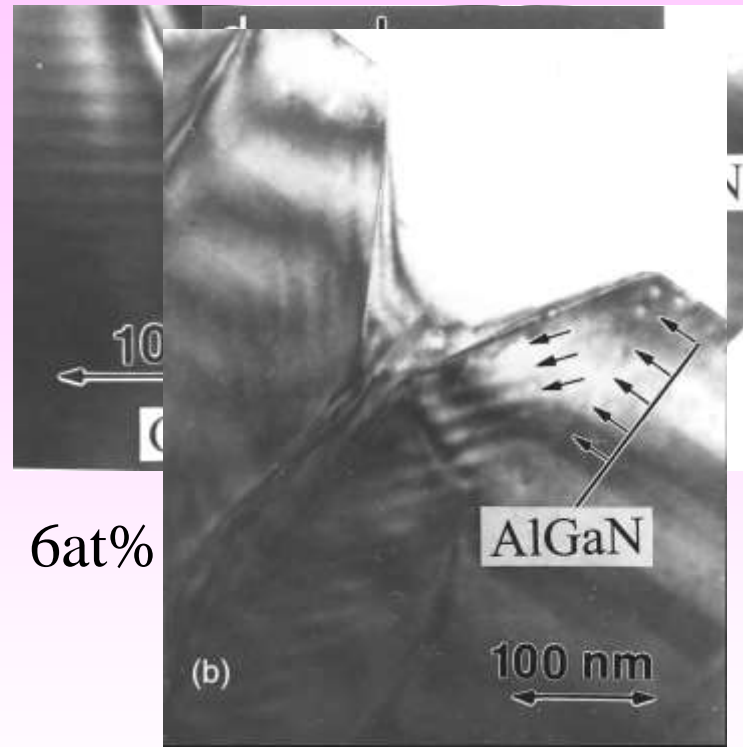
N. Vouroutzis, J. Stoemenos, N. Frangis, G.Z. Radnóczy, D. Knez, F. Hofer and B. Pécz under review at Scientific Reports



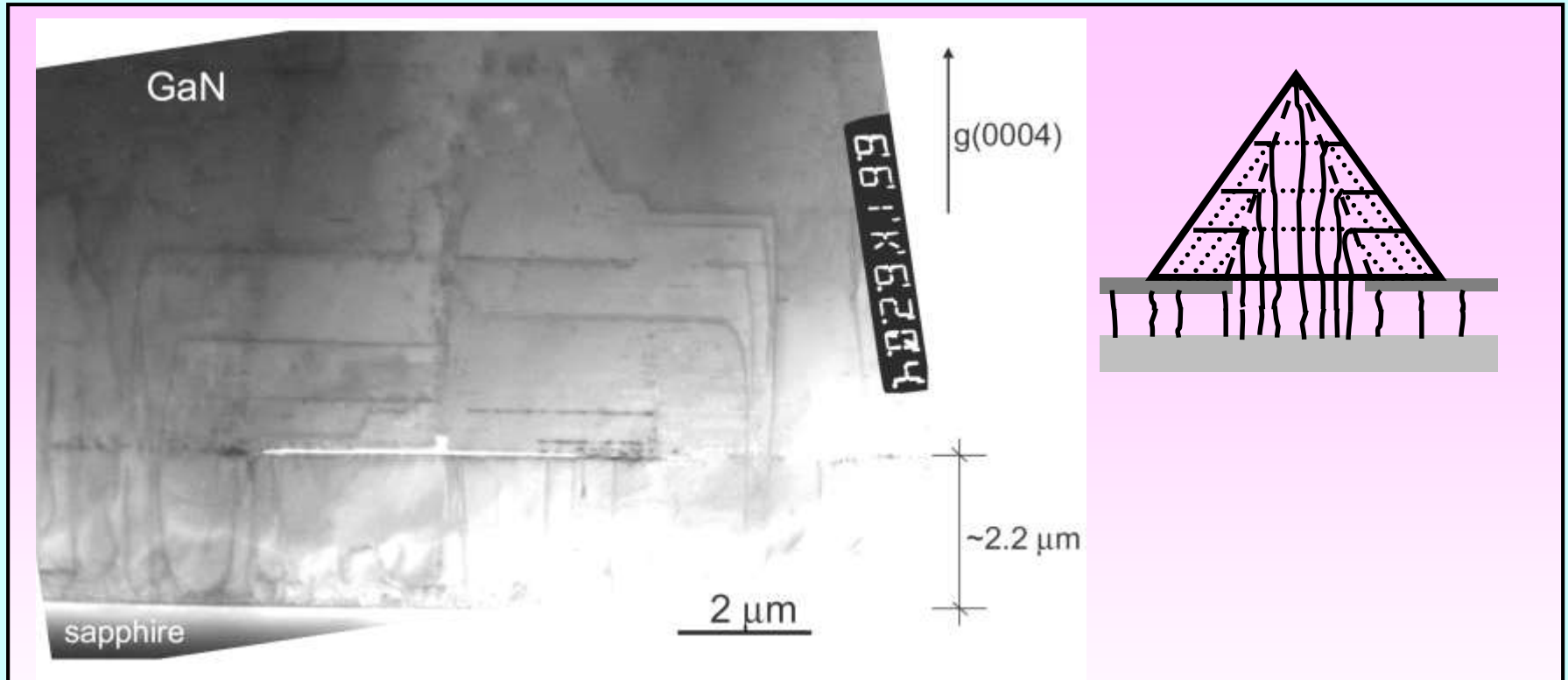
GaN with dislocation density of $4 \times 10^9 \text{ cm}^{-2}$

B. Pécz et al. J. Appl. Phys., 86 (1999) 6059-6067

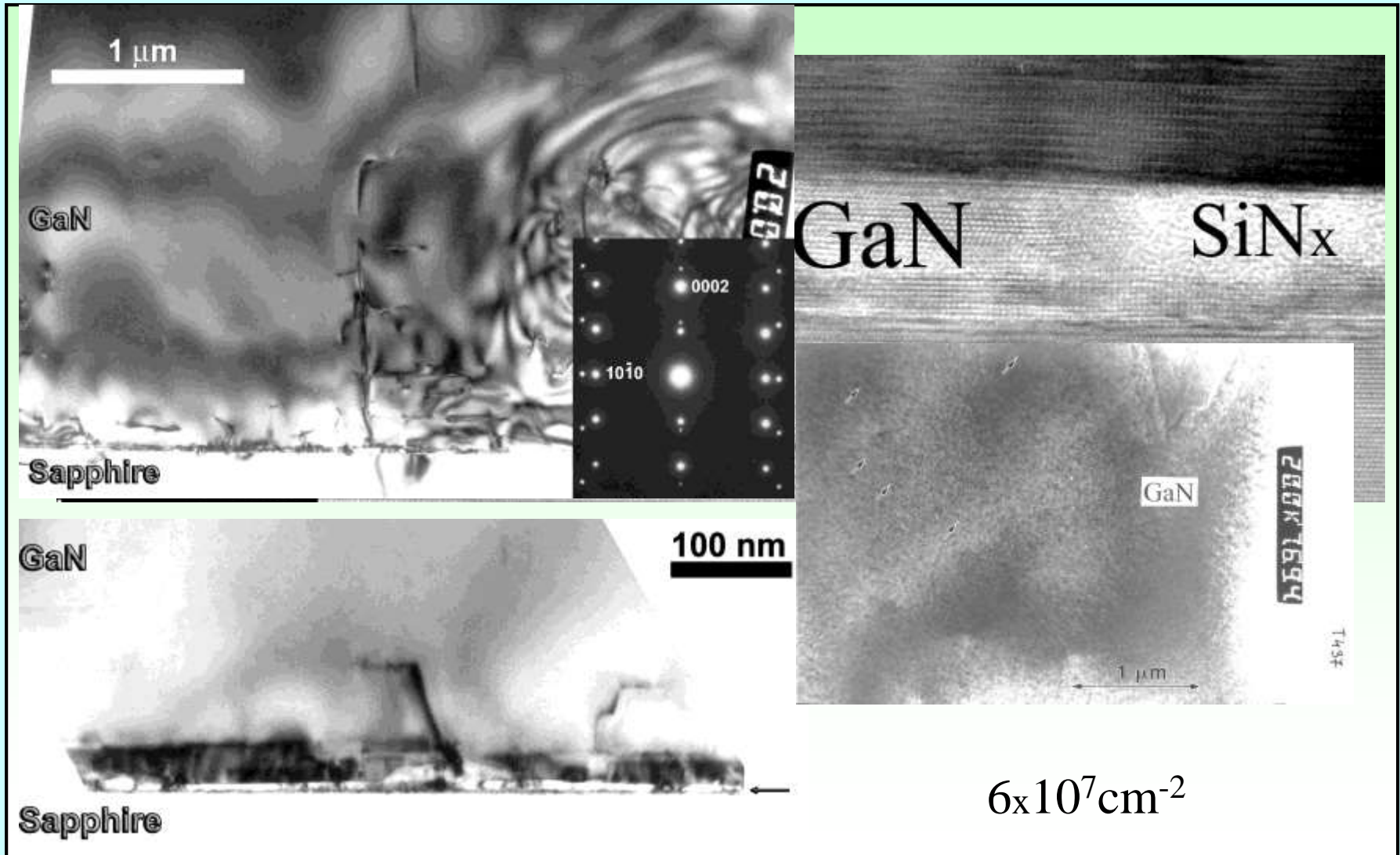
AlGaN/GaN superlattice

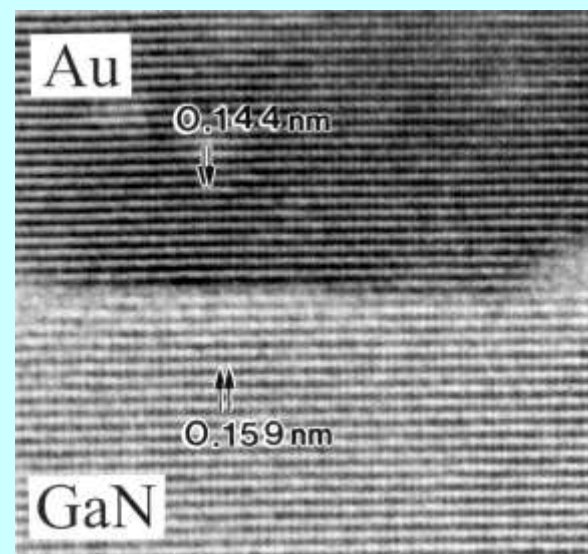
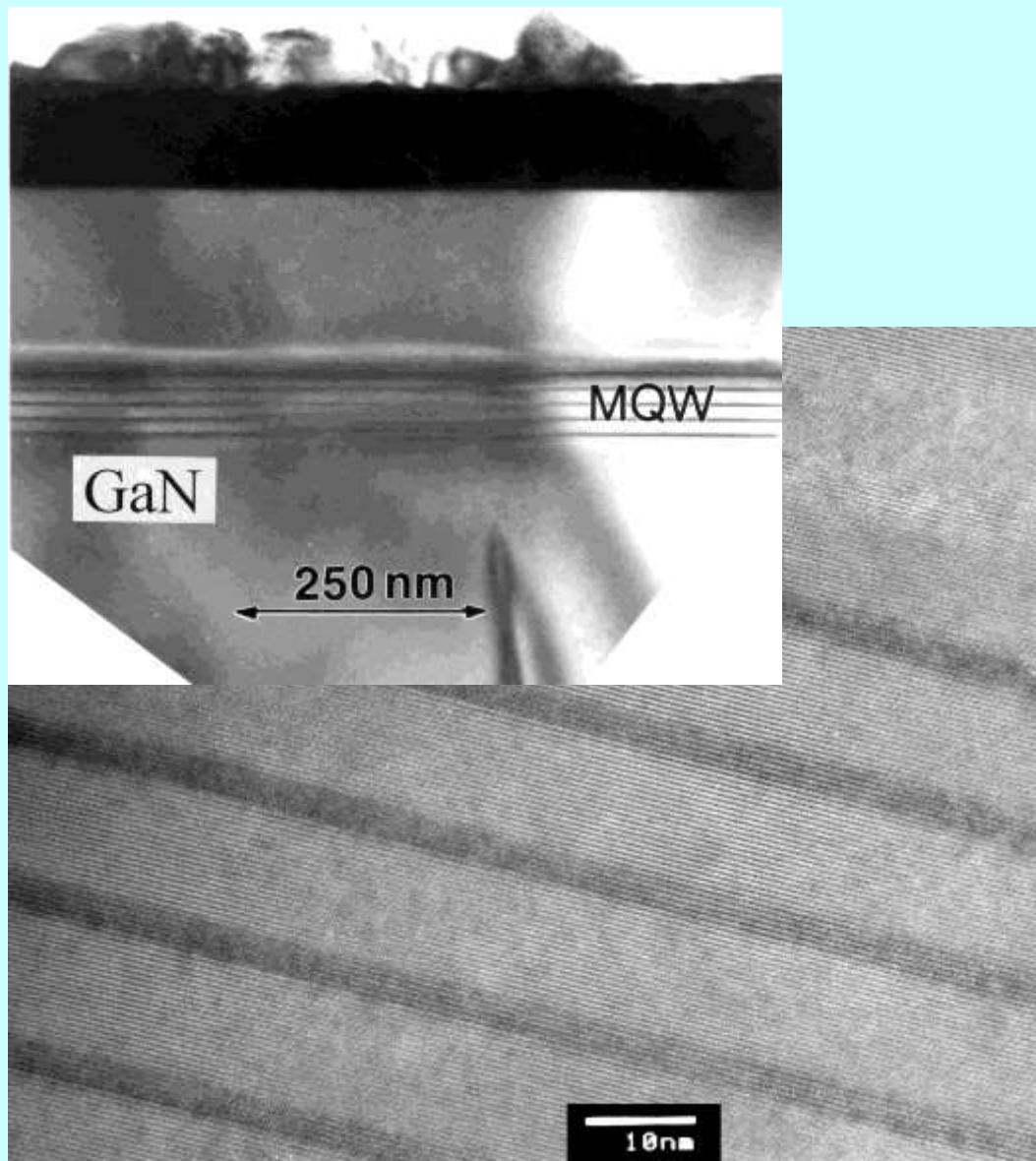


B. Pécz, Zs. Makkai, M. A. di Forte-Poisson, F. Huet and R. E. D'Amico, J. Polkowiński
V-shaped defects connected to inversion domains in AlGaN layer
Appl. Phys. Lett. 78 (2001) 1529-1531



dislocations are bent and defect density is decreased also in window





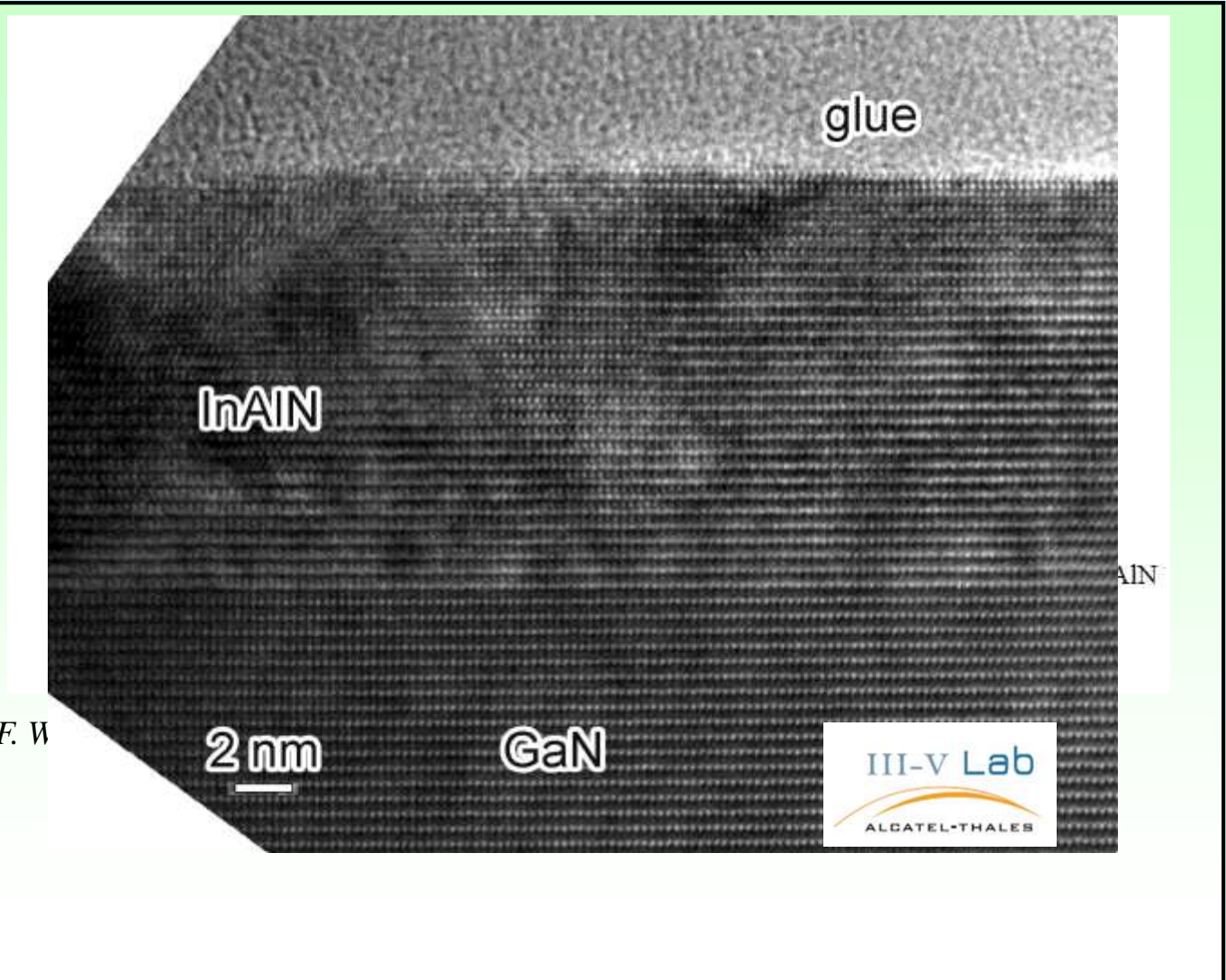
p-GaN(Mg)	0.5 μ m
p-Al _{0.15} Ga _{0.85} N (Mg)	0.15 μ m
n-In _{0.06} Ga _{0.94} N (Mg,Zn)	0.05 μ m
n-Al _{0.15} Ga _{0.85} N (Si)	0.15 μ m
n-GaN (Si)	4 μ m
GaN puffer	0.03 μ m
sapphire	

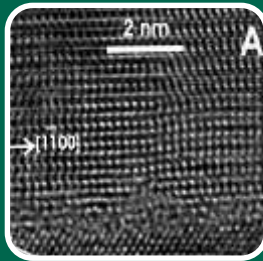
**LED prepared by
Nakamura**

OSRAM blue laser diode
based on InGaN, 2000

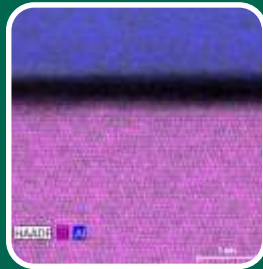
Typical HEMT
structure
to 160 GHz
10 W/mm

U.K. Mishra, P. Parikh, Y.F. W



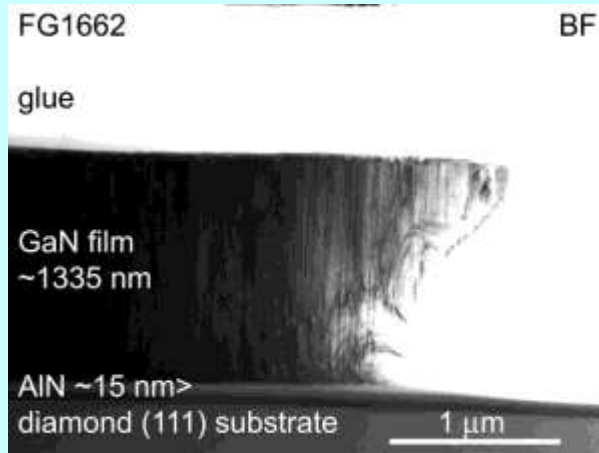


GaN HEMT grown on diamond

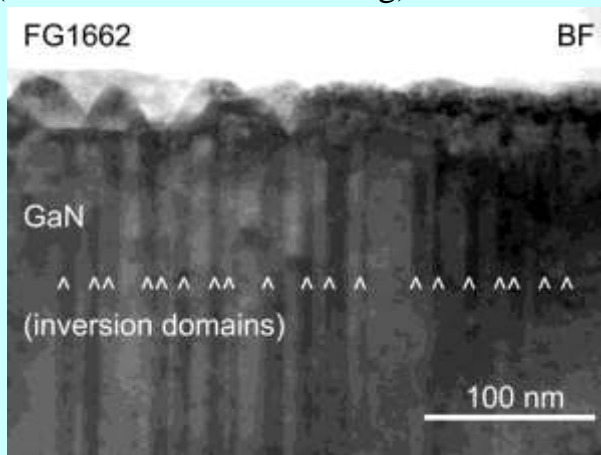


integration of graphene sheets
into nitride devices

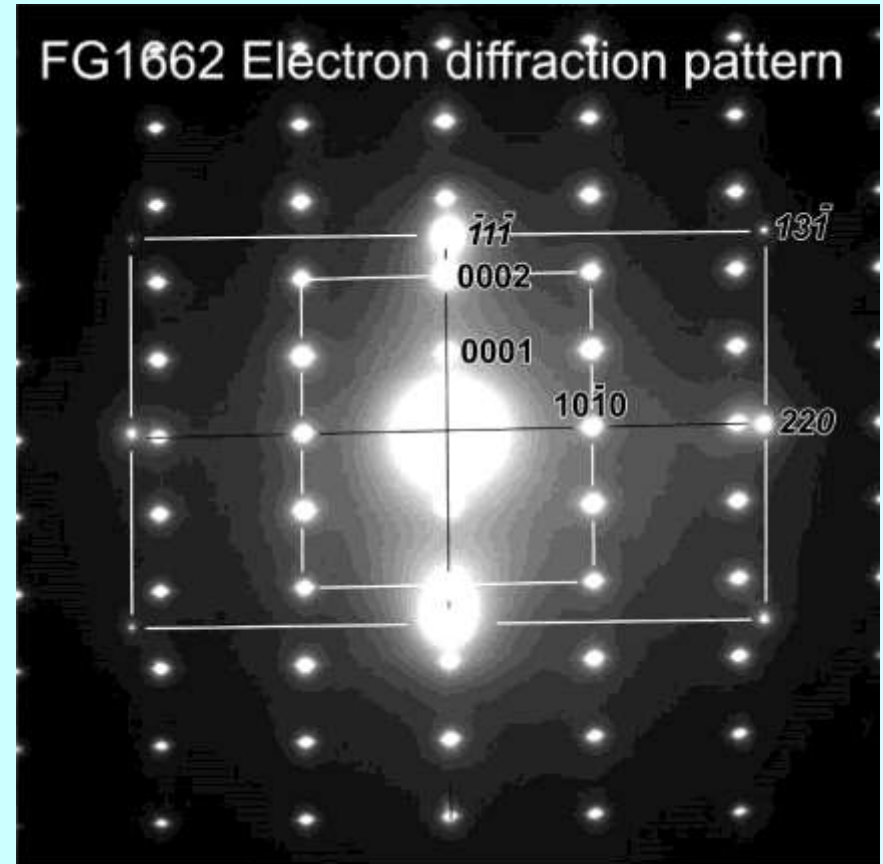
GaN grown on diamond (111)



overview of the entire layer
(left after chemical etching)



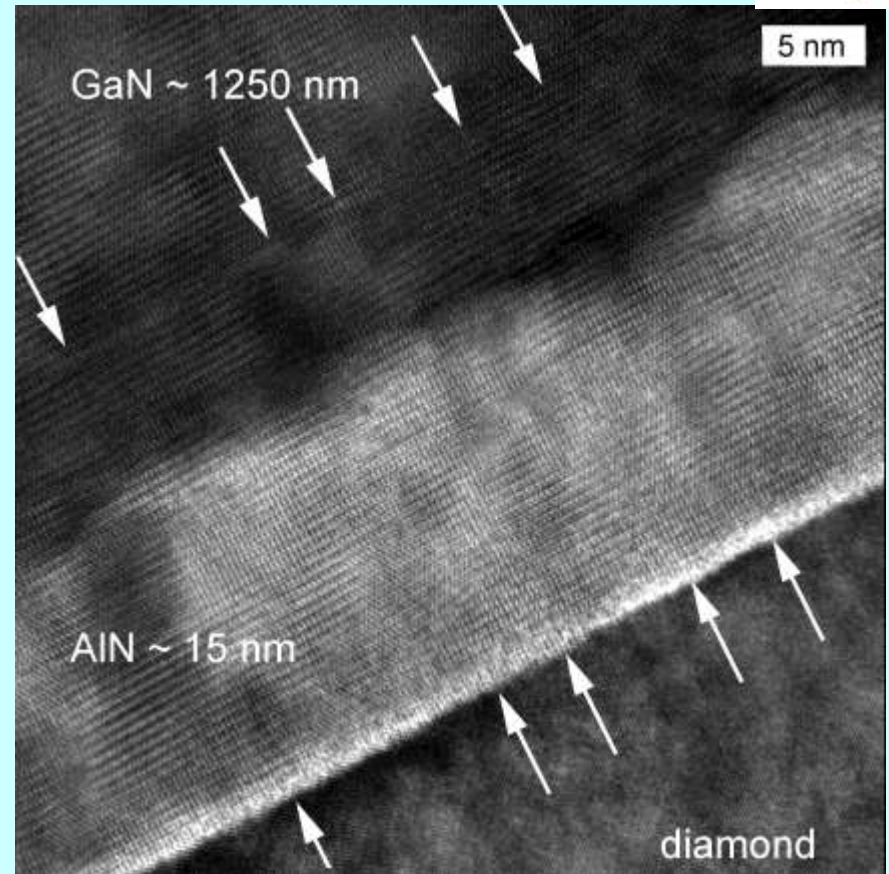
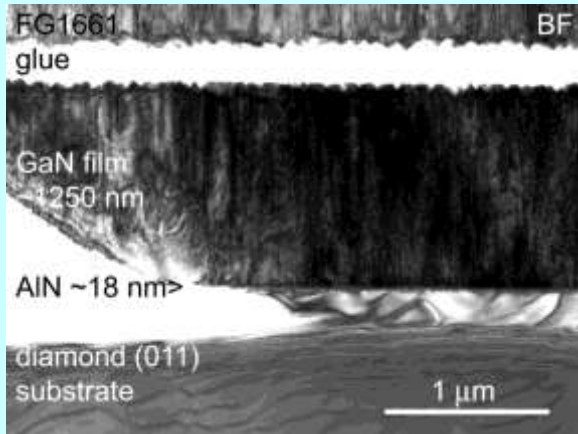
numerous inversion domains close to the surface



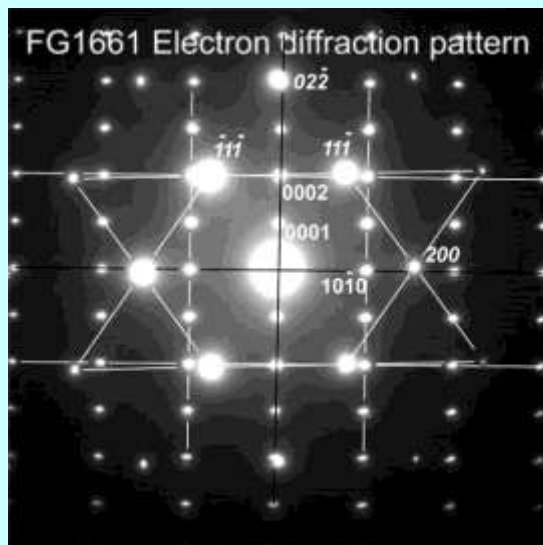
Epitaxy:

(0002)GaN//(111)diamond
and (1010)GaN//(220)diamond.

GaN grown on diamond (110)



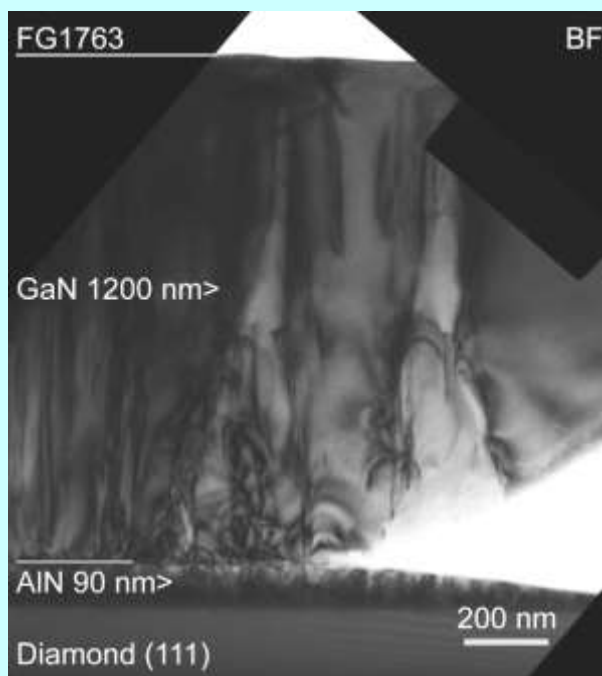
overview of the entire layer
(after chemical etching)



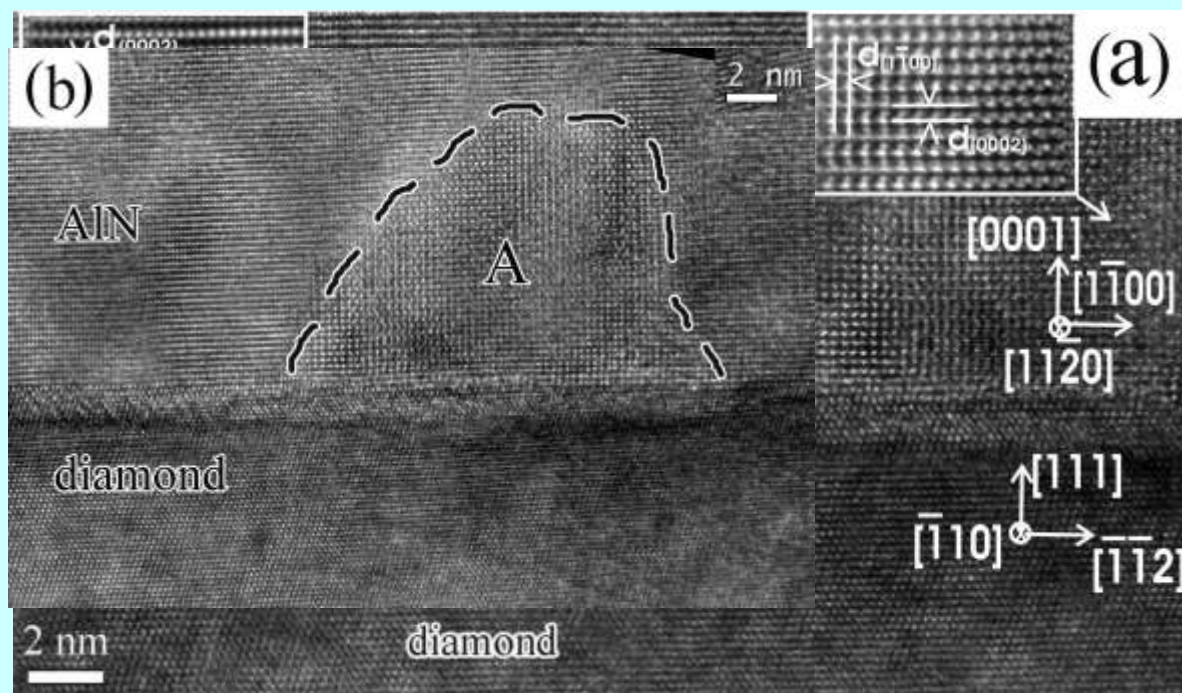
IDs are formed on the surface of diamond during the AlN growth

B. Pécz et al.: GaN heterostructures with diamond and graphene, Semicond. Sci. Technol. 30 (2015) 114001 (6pp)

GaN grown on diamond (111)

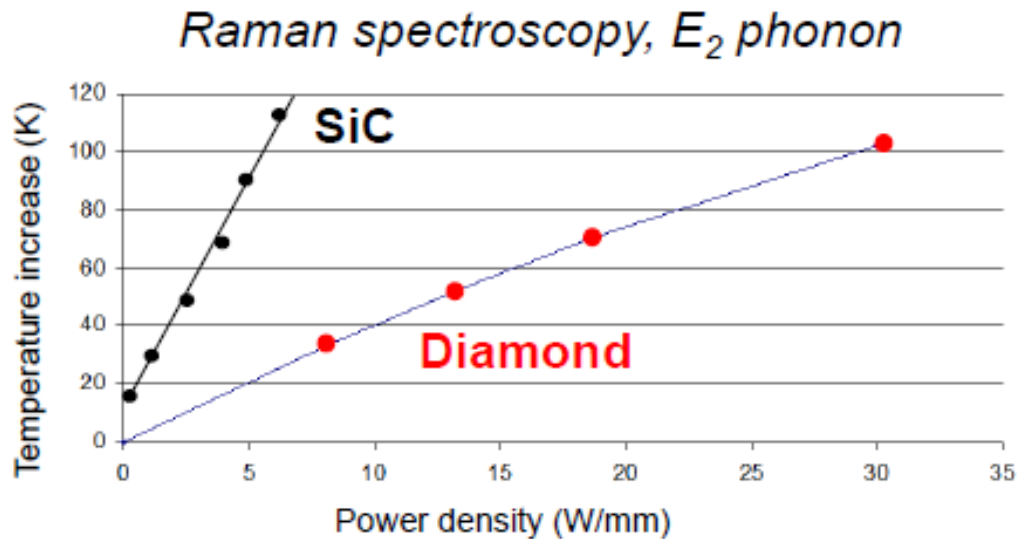


Nitridation suppressed the formation of IDs.
60 min at 150°C



B. Pécz et al.
Diamond & Related
Materials 34 (2013) 9–12

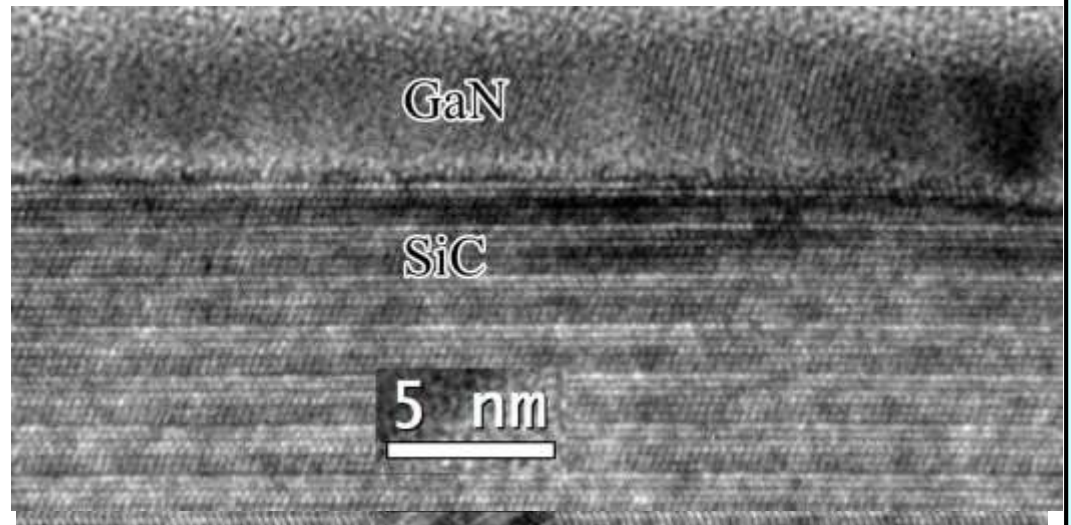
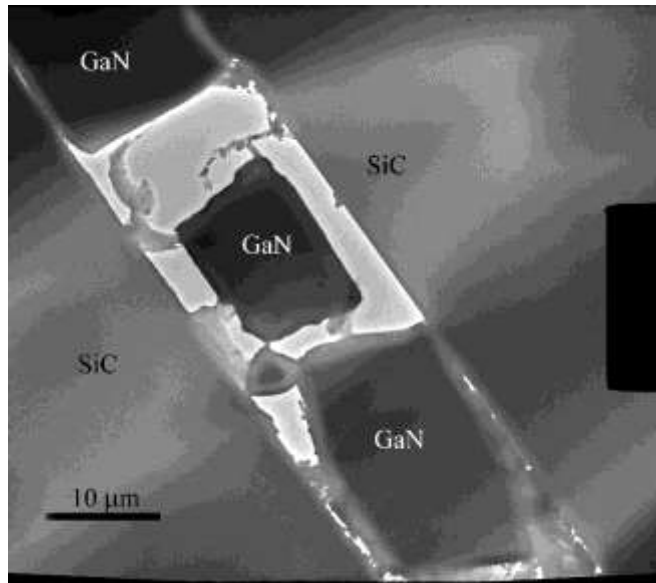
AlGaN/GaN HEMT Grown by Nitride MBE on (111) Diamond

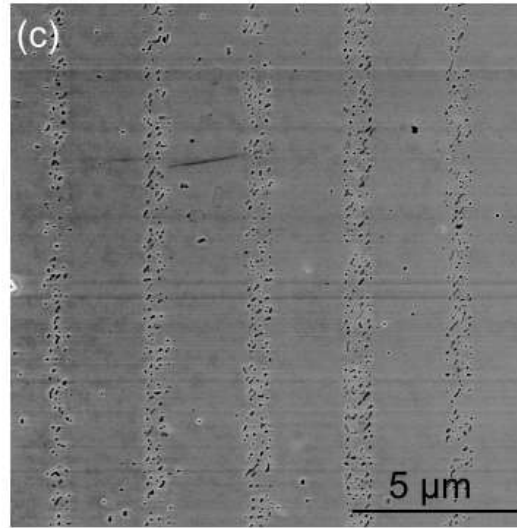
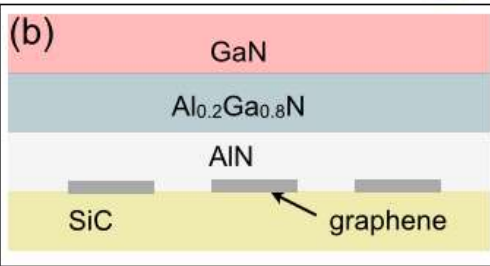
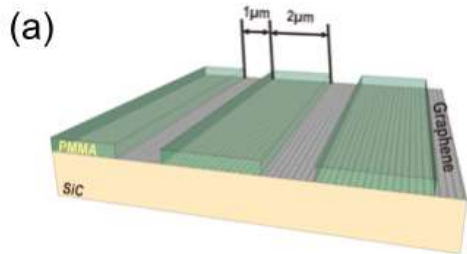


M. Alomari et al.; *Electronic Lett.*, 46 (2010), 299

integration of graphene sheets into nitride devices

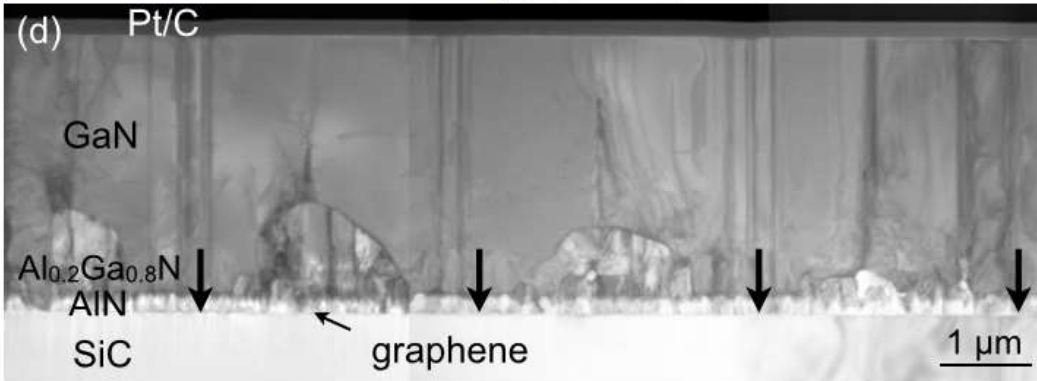
Direct growth onto graphene failed.





smooth surface

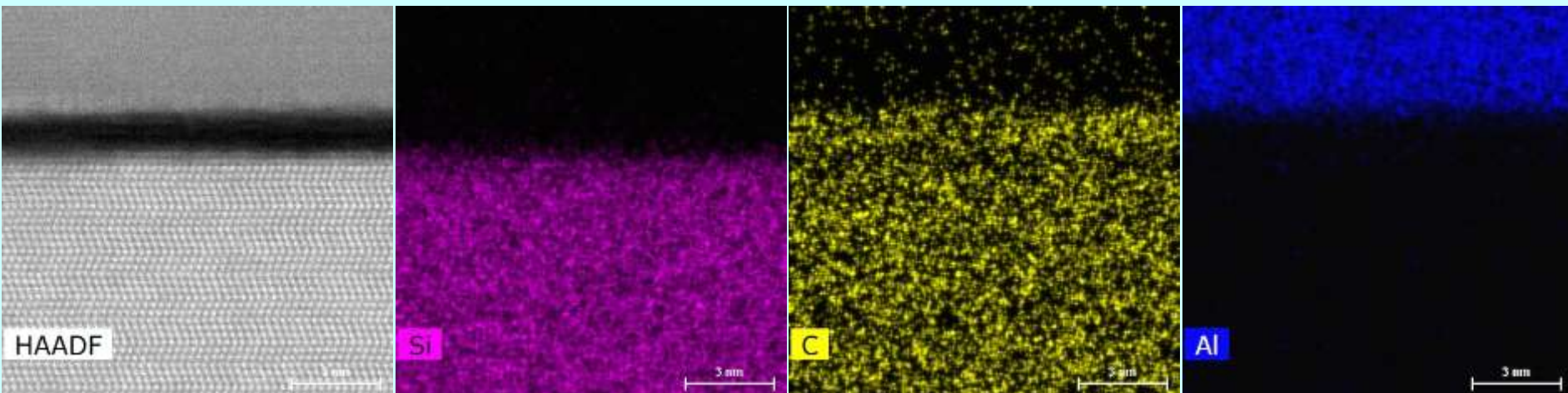
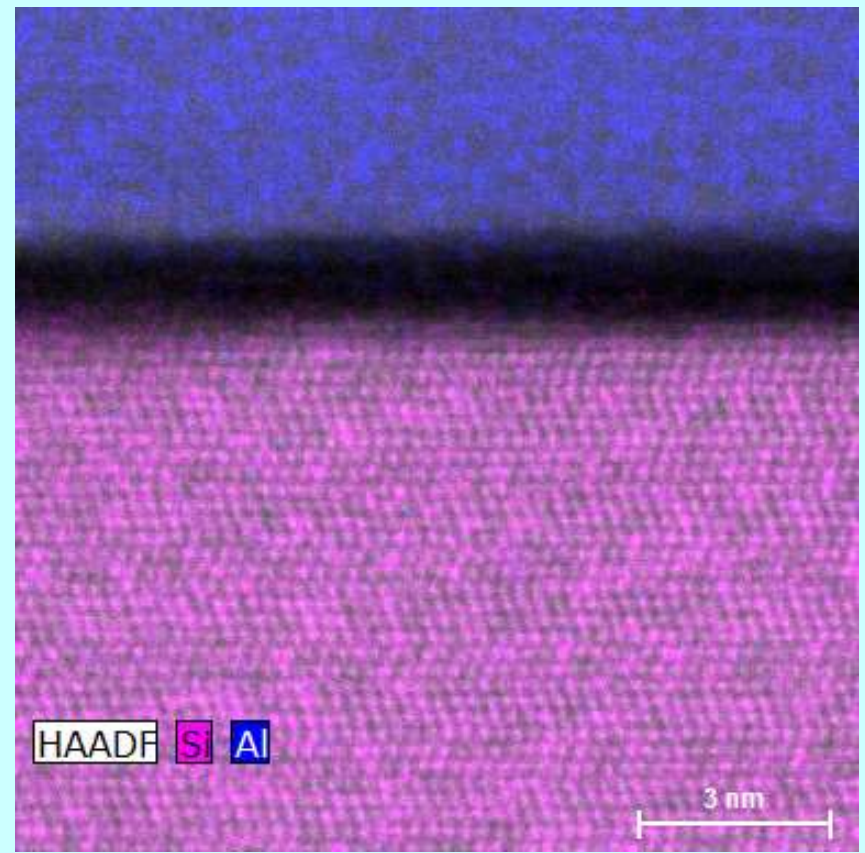
dislocation density
 $\sim 3 \times 10^9 \text{ cm}^{-2}$



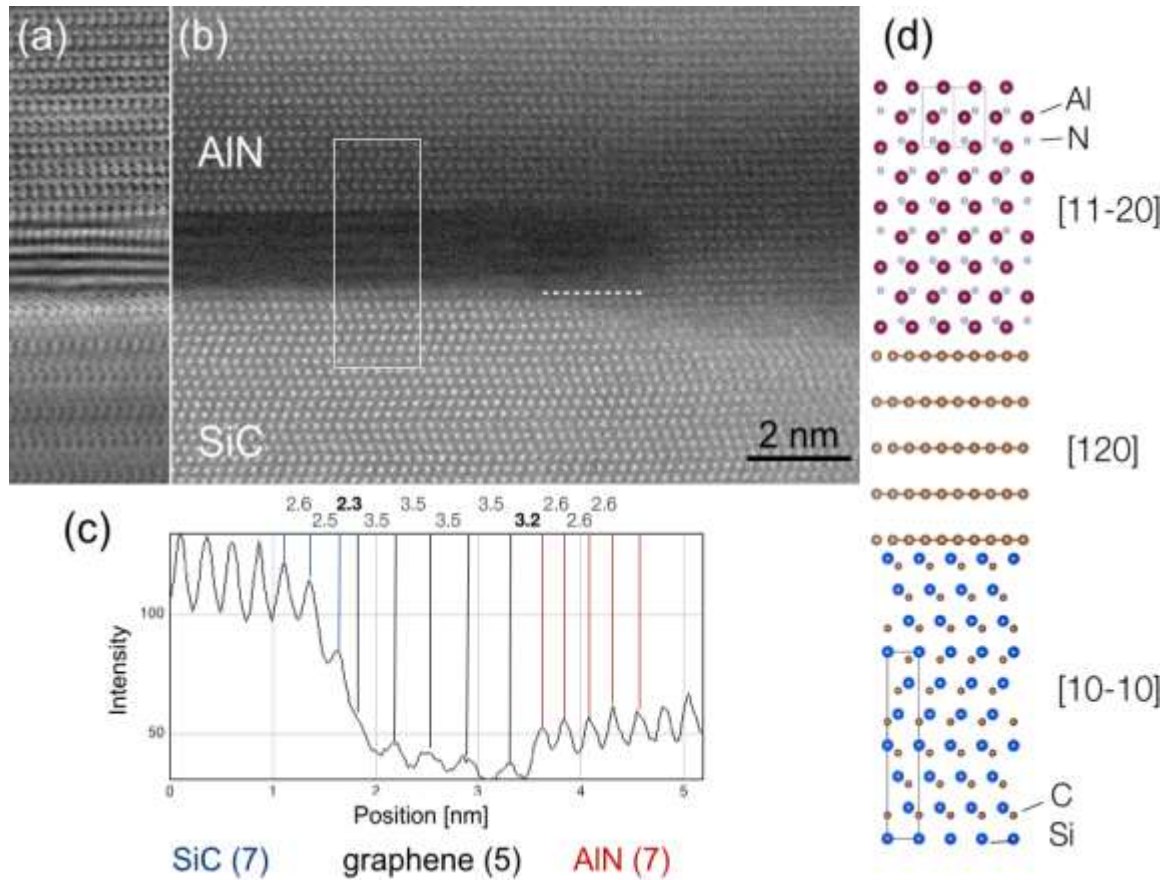
A. Kovács, M. Duchamp, R.E. Dunin-Borkowski, R. Yakimova, P. L. Neumann, H. Behmenburg, B. Foltynski, C. Giesen, M. Heuken and B. Pécz: Graphoepitaxy of High-Quality GaN Layers on Graphene/6H-SiC, *Advanced Materials Interfaces*, 2 (2015) DOI: 10.1002/admi.201400230

AlN growth on continuous graphene

Al and Si EDXS maps superimposed onto a HAADF STEM image

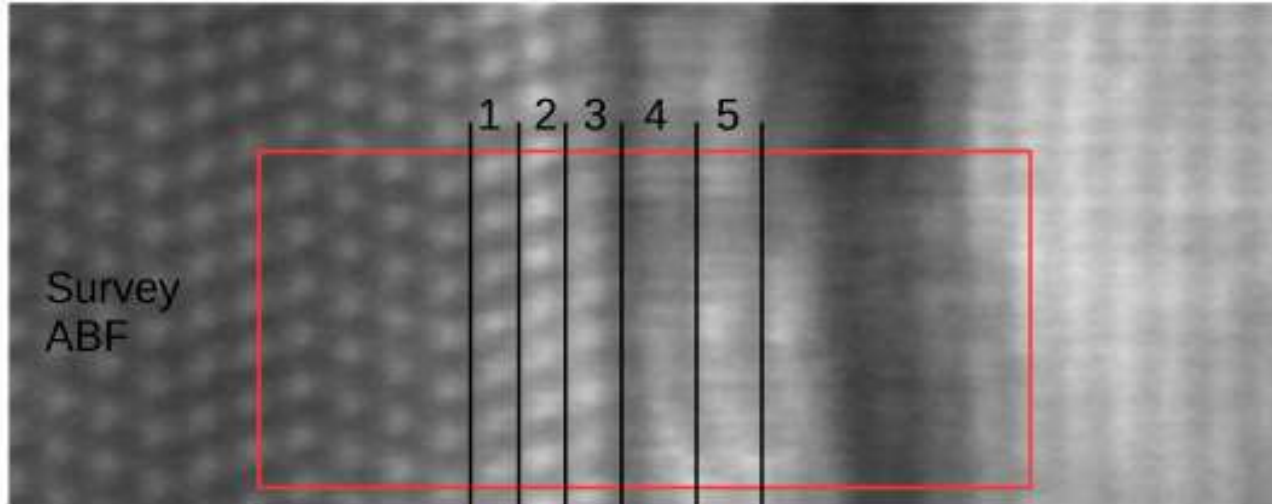


HAADF STEM image, Si, C and Al EDXS maps recorded using a FEI Titan ChemiSTEM at 200 kV.

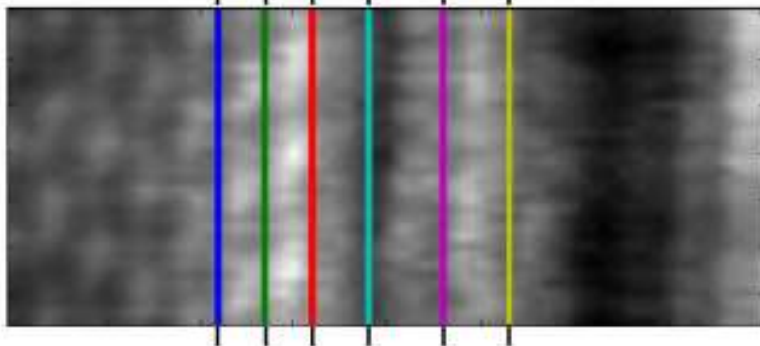


typically 3 layers of graphene, but sometimes 5 are observed

017 Interface



Live
ABF

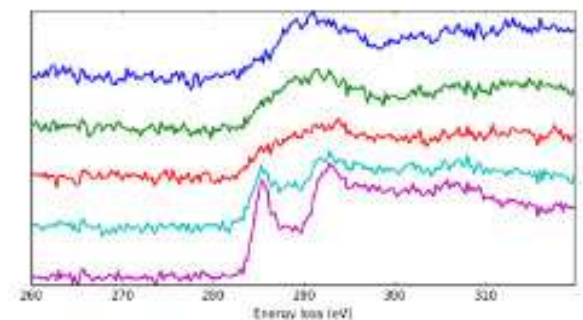
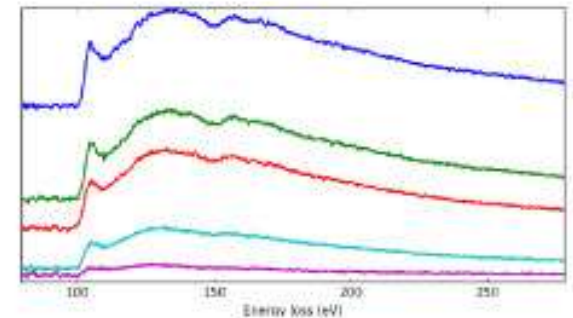
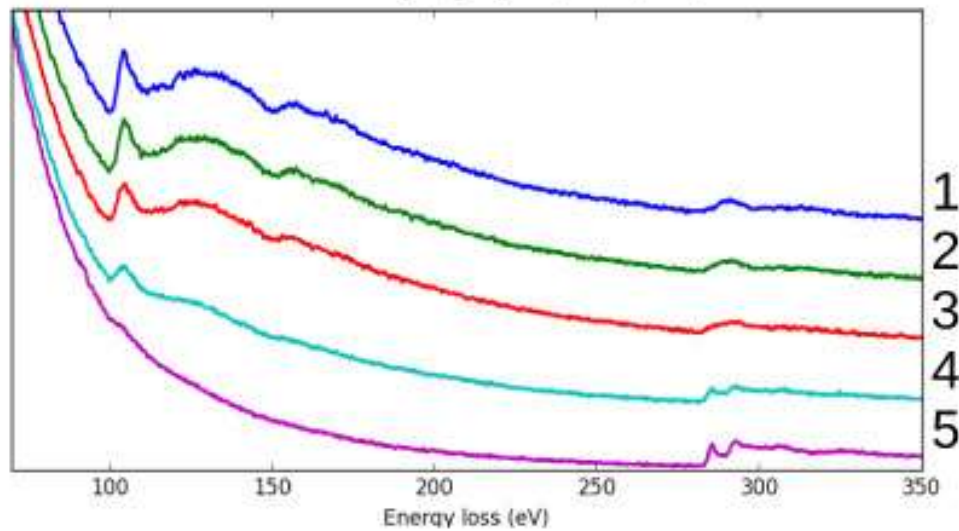


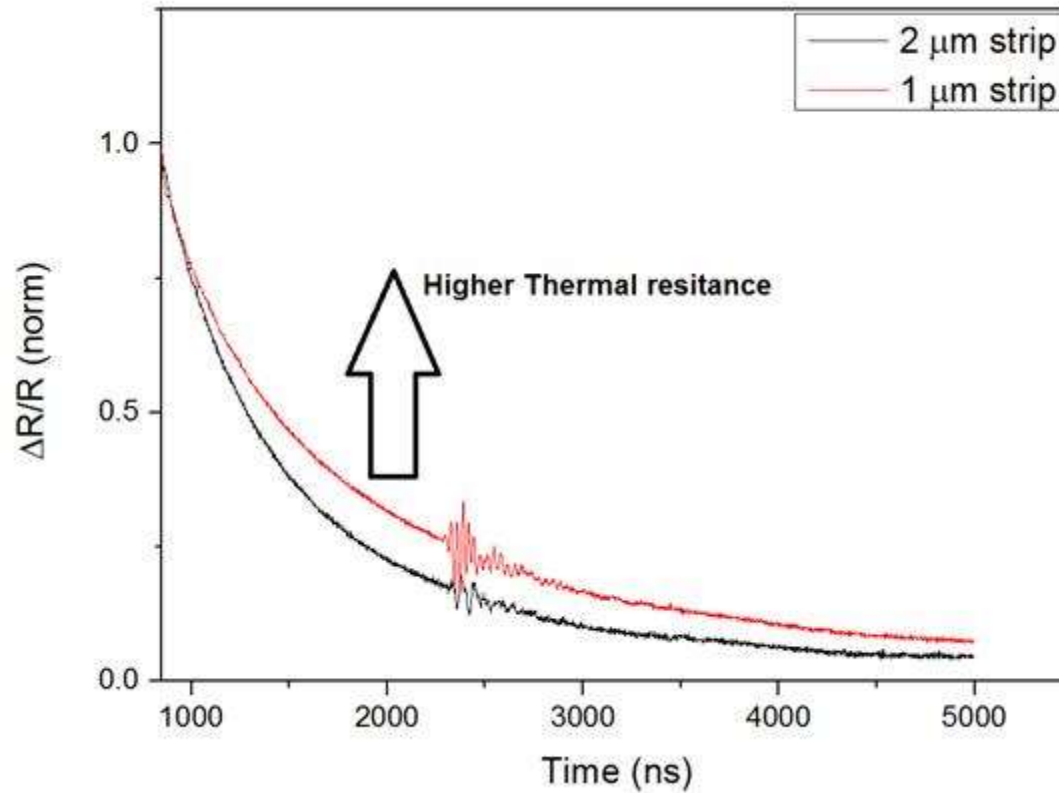
Carbon K edge

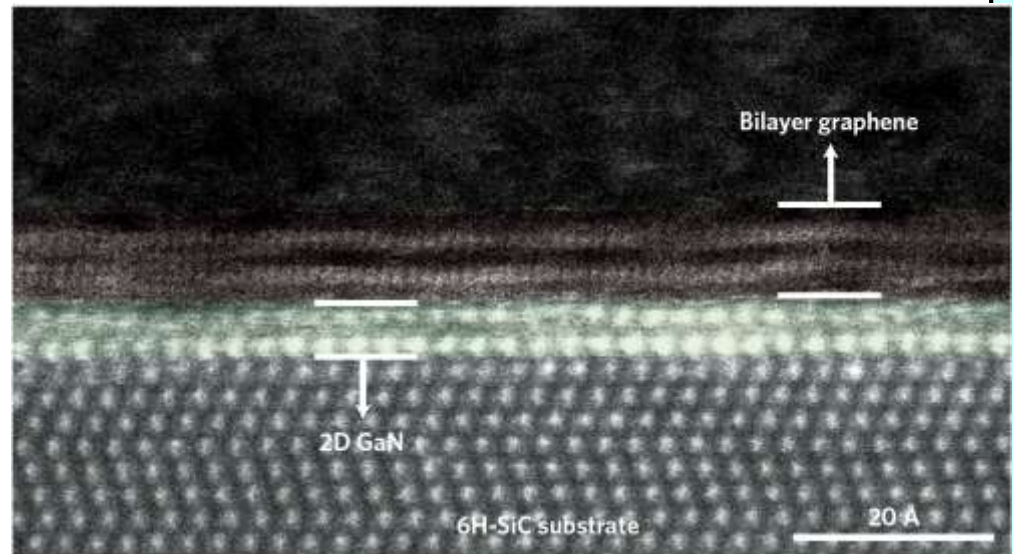
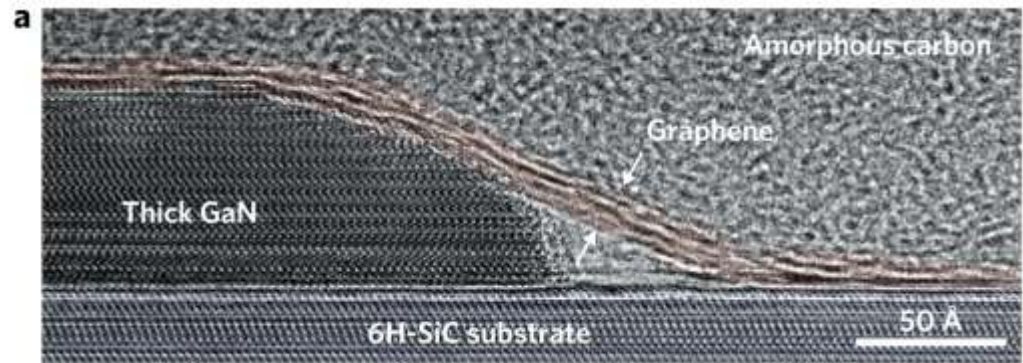
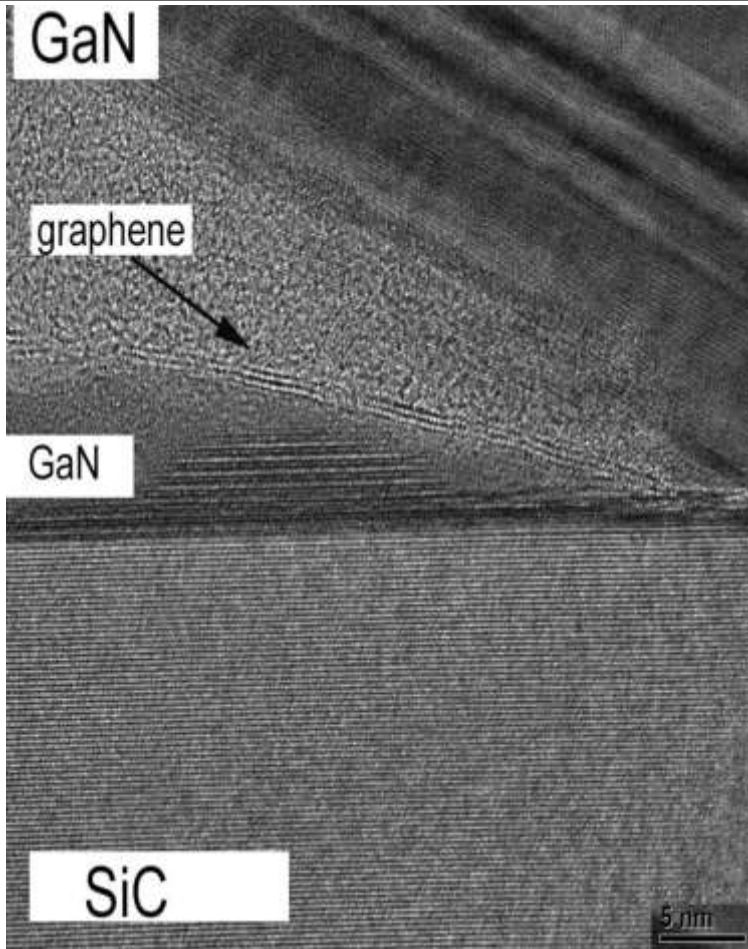
Layer 1 and 2: sigma only

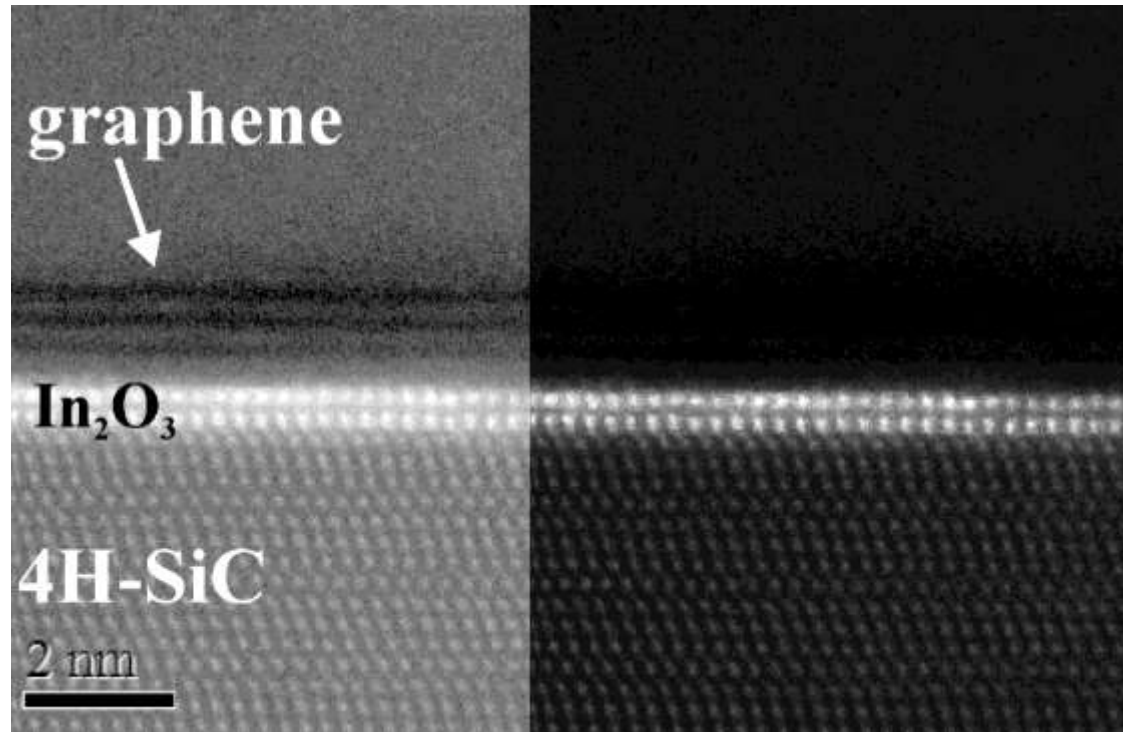
Layer 3: soft pi and sigma

Layer 4 and 5: strong pi and sigma

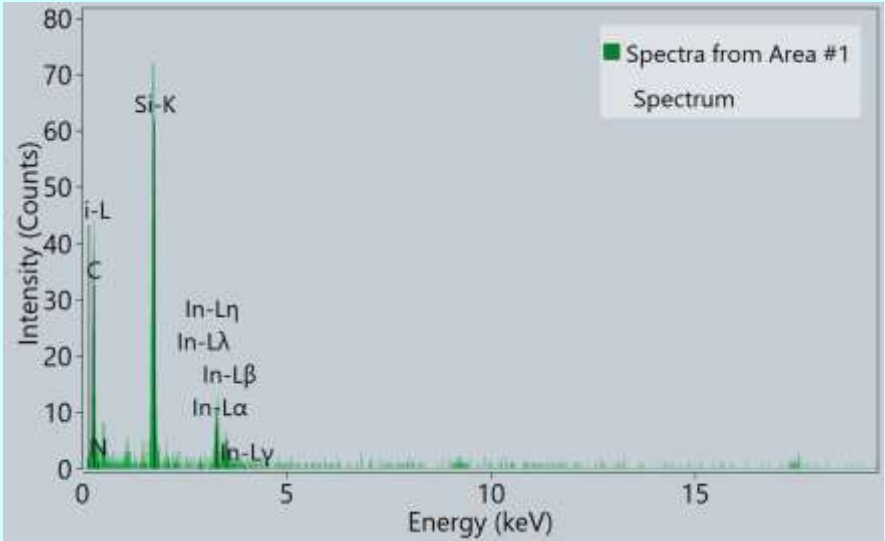
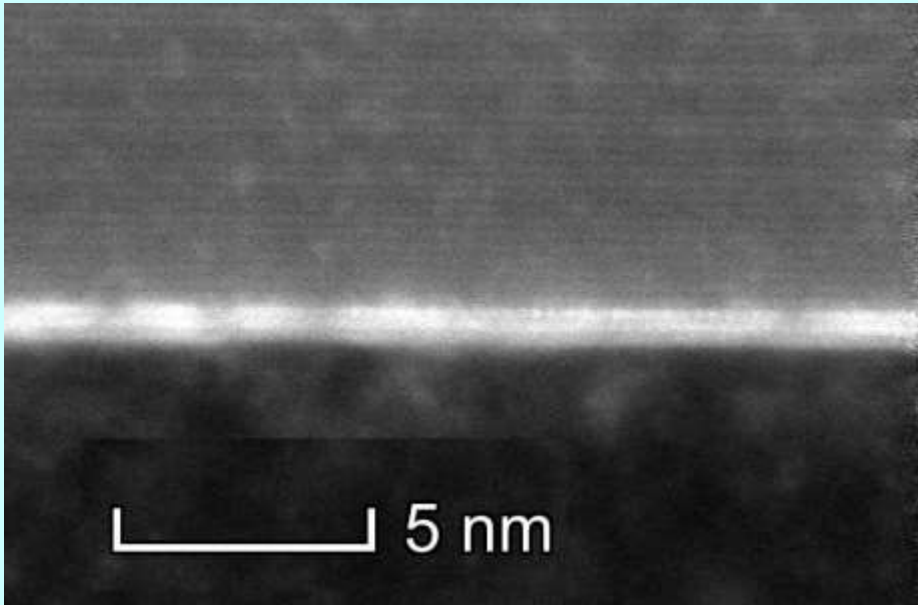
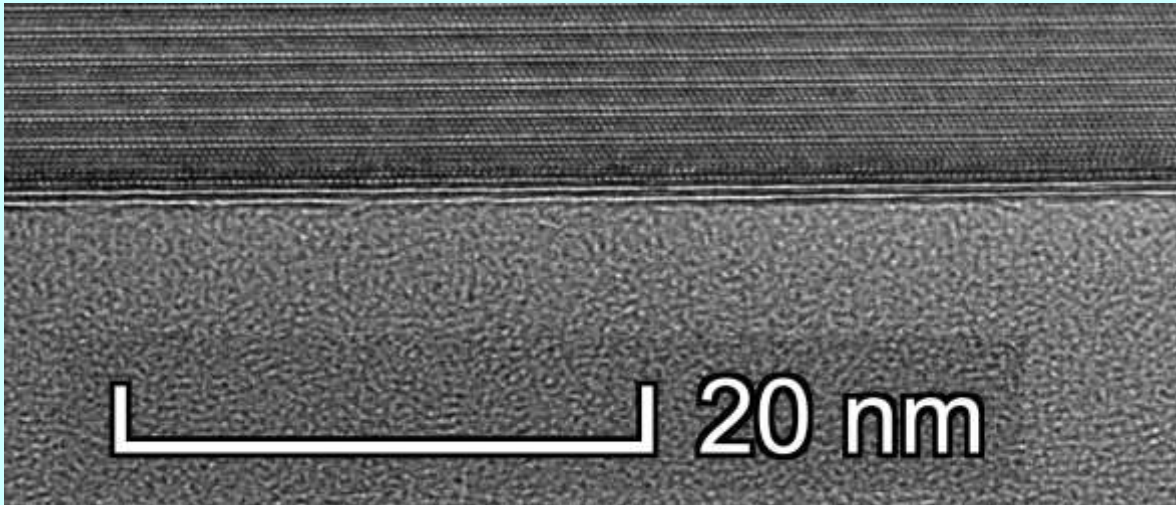




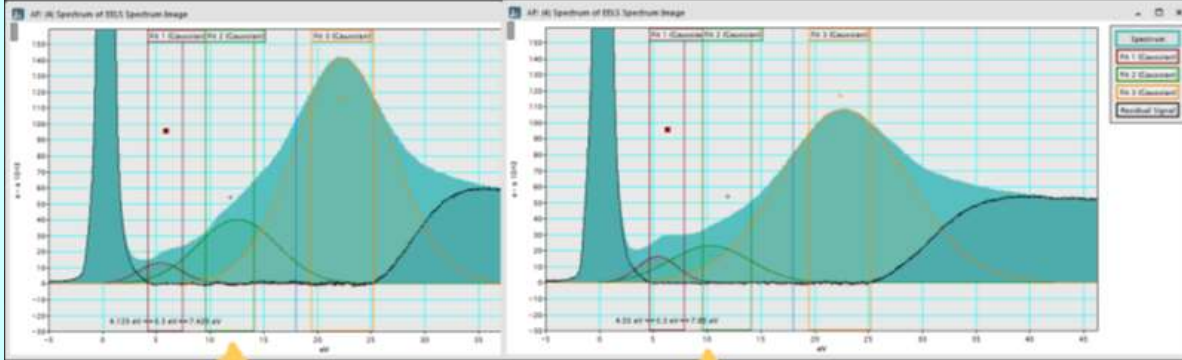




In_2O_3 2D semiconductor intercalated



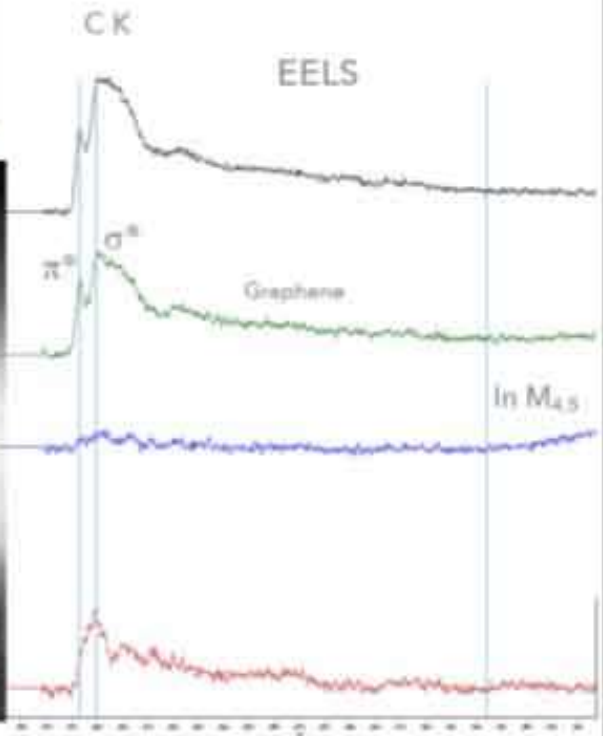
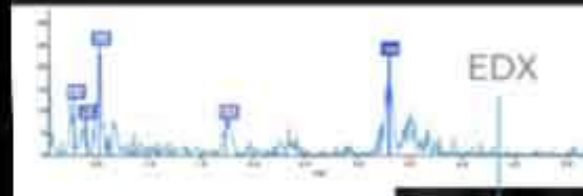
3 layers of InN



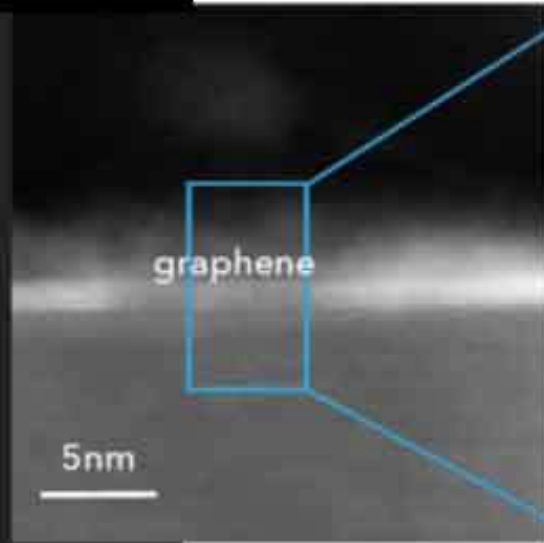
11.7eV



10eV

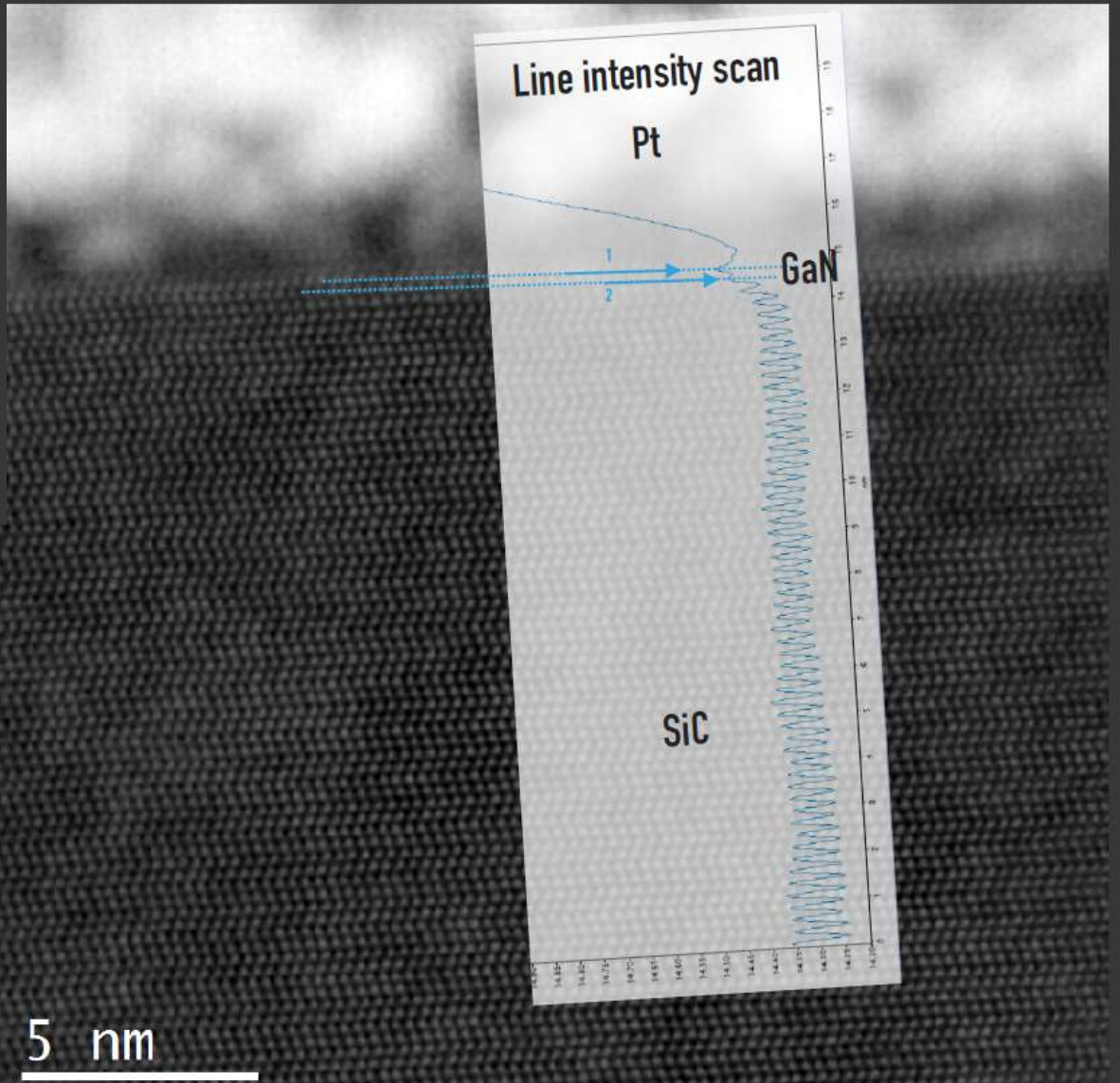
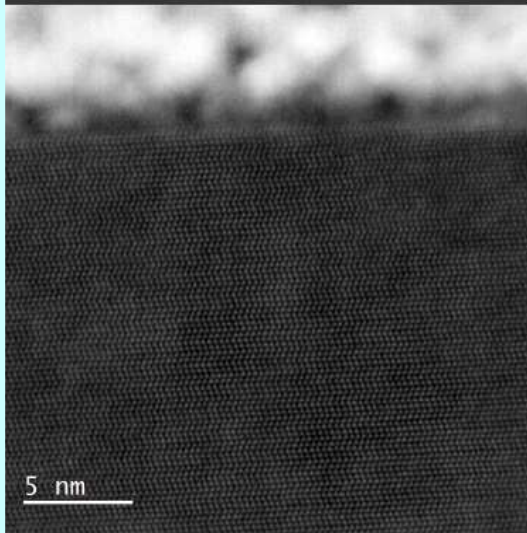
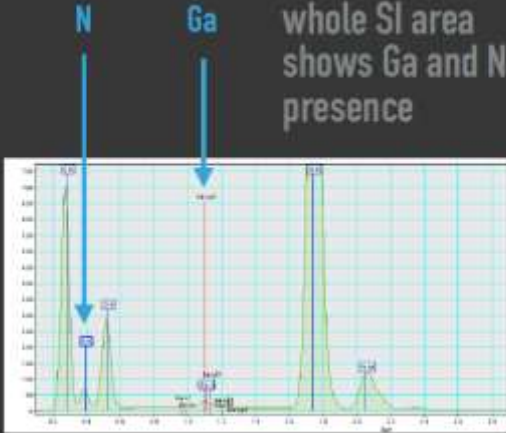


HAADF

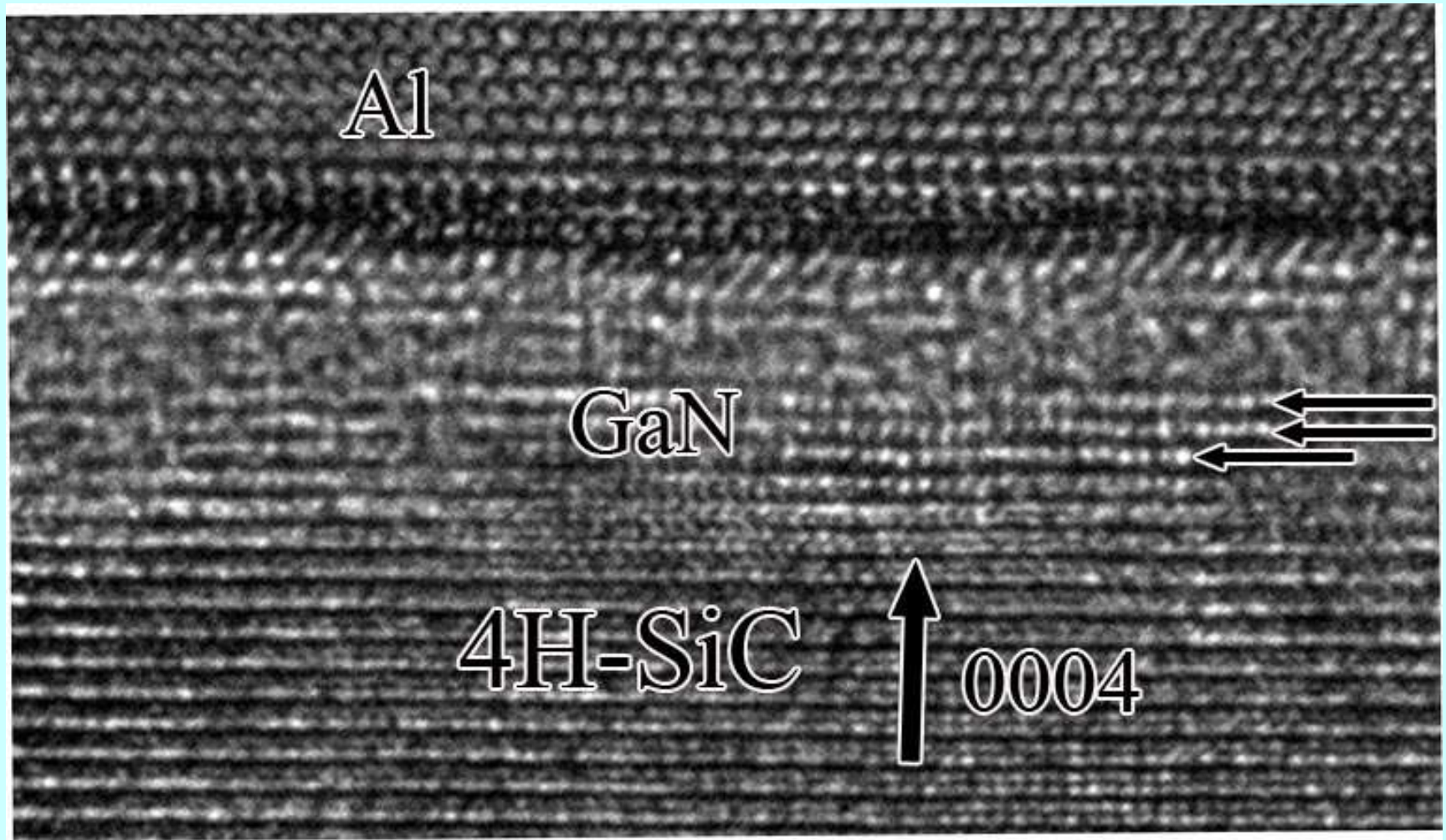


HAADF Z-CONTRAST S/TEM @60KEV

EDX spectrum
integrated over the
whole SI area
shows Ga and N
presence



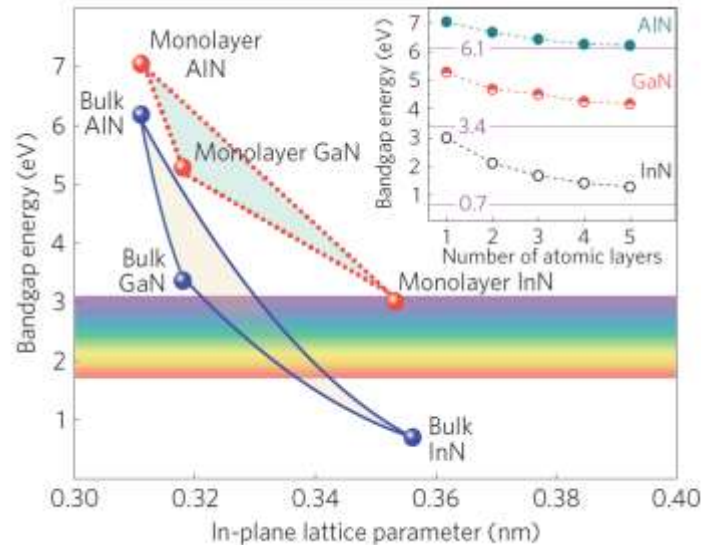
HRTEM



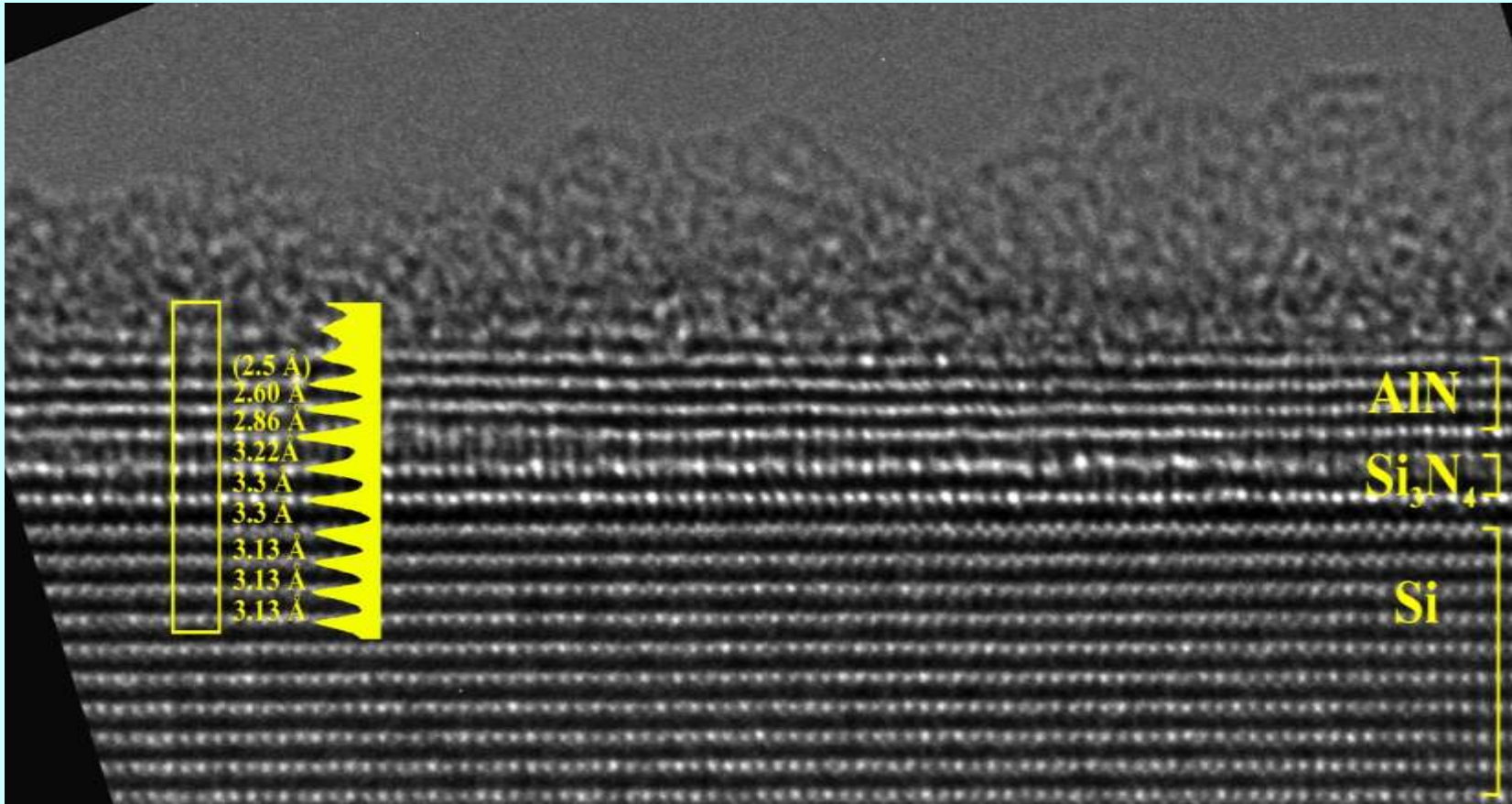
Summary and outlook:

Microscopy is useful in the research of compound semiconductors

2D nitrides will be grown with different properties (bandgap)



This work is supported by the FLAG ERA GRIFONE project, No.: NN 118914 VEKOP-2.3.3-15-2016-00002 of the European Structural and Investment Funds



3 eV
2.2 eV

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Thank you for your attention!

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